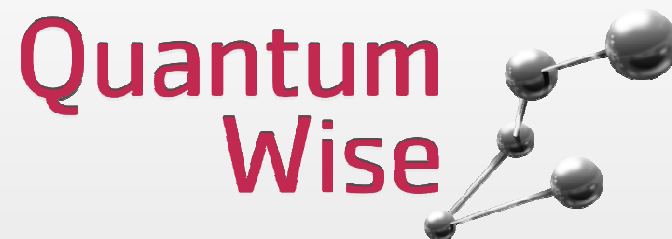


Electronic structure theory on the world market

Kurt Stokbro, QuantumWise A/S

Kurt Stokbro

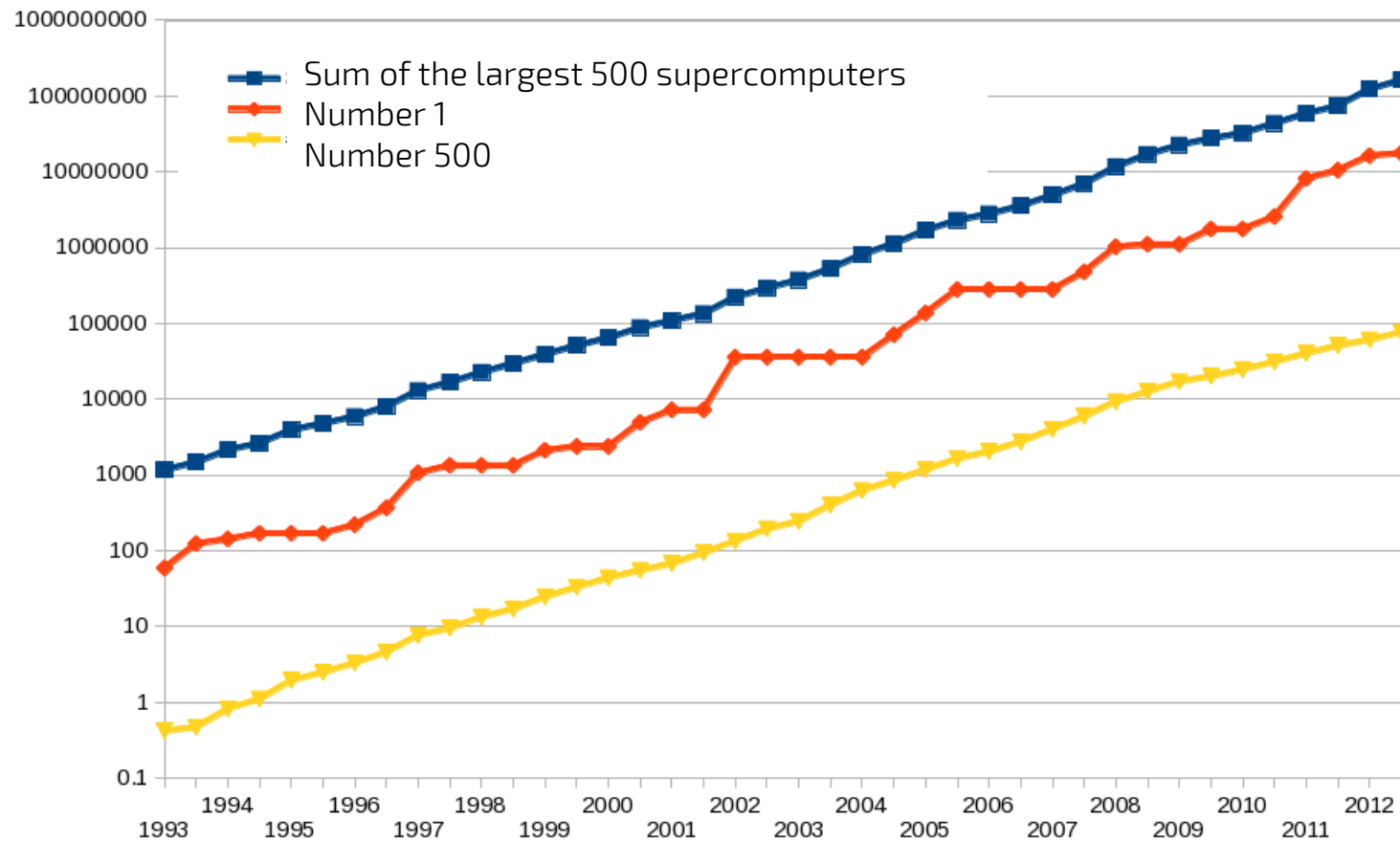




Most cited papers in APS (from 1893)

	Journal	# cites	Title	Author(s)
1	PRB (1988)	39190	Development of the Colle-Salvetti Correlation-Energy ...	Lee, Yang, Parr
2	PRL (1996)	25452	Generalized Gradient Approximation Made Simple	Perdew, Burke, Ernzerhof
3	PRA (1988)	22904	Density-Functional Exchange-Energy Approximation ...	Becke
4	PR (1965)	20142	Self-Consistent Equations Including Exchange and Correlation ...	Kohn and Sham
5	PRB (1996)	13731	Efficient Iterative Schemes for Ab Initio Total-Energy ...	Kresse and Furthmuller
6	PRB (1976)	13160	Special Points for Brillouin-Zone Integrations	Monkhorst and Pack
7	PRB (1992)	10876	Accurate and Simple Analytic Representation of the Electron ...	Perdew and Wang
8	PRB (1999)	10007	From Ultrasoft Pseudopotentials to the Projector Augmented ...	Kresse and Joubert
9	PRB (1990)	9840	Soft Self-Consistent Pseudopotentials in a Generalized ...	Vanderbilt
10	PR (1964)	9789	Inhomogeneous Electron Gas	Hohenberg and Kohn
11	PRB (1981)	9787	Self-Interaction Correction to Density-Functional Approx. ...	Perdew and Zunger
12	PRB (1992)	9786	Atoms, Molecules, Solids, and Surfaces - Applications of the ...	Perdew, Chevary, ...
13	PRB (1986)	9313	Density-Functional Approx. for the Correlation-Energy ...	Perdew
14	PR (1934)	9271	Note on an Approximation Treatment for Many-Electron Systems	Moller and Plesset
15	PRB (1994)	9100	Projector Augmented-Wave Method	Bloch
16	PRL (1980)	7751	Ground-State of the Electron-Gas by a Stochastic Method	Ceperley and Alder
17	PRL (1987)	7663	Inhibited Spontaneous Emission in Solid-State Physics ...	Yablonovitch
18	PRL (1986)	7589	Atomic Force Microscope	Binnig, Quate, Gerber
19	PRB (1991)	7425	Efficient Pseudopotentials for Plane-Wave Calculations	Troullier and Martins
20	PRB (1993)	6925	Ab initio Molecular Dynamics for Liquid Metals	Kresse and Hafner
21	PR (1961)	6467	Effects of Configuration Interaction on Intensities and Phase Shifts	Fano
22	PR (1957)	6260	Theory of Superconductivity	Bardeen, Cooper, Schrieffer

Computing power 1993-2013



Computing power doubles every 14 months

Questions



Who are using electronic structure methods ?

Academia/Industry

What are they using the tools for ?

Application areas

How to answer these questions?

- ❖ Stastics summer school
- ❖ Statistics of publications
- ❖ *"The economic impact of molecular modelling of chemicals and materials"*, Goldbeck consulting
- ❖ QuantumWise user base

Participants at summer school



2014: 125 participants
29 nationalities

Denmark	33
China	11
Germany	10
Italy	8
United States	8
India	7
France	6
Iceland	4
Spain	4
United Kingdom	4
Finland	3

Europe 66%
Male 82 %

2016: 161 participants
35 nationalities

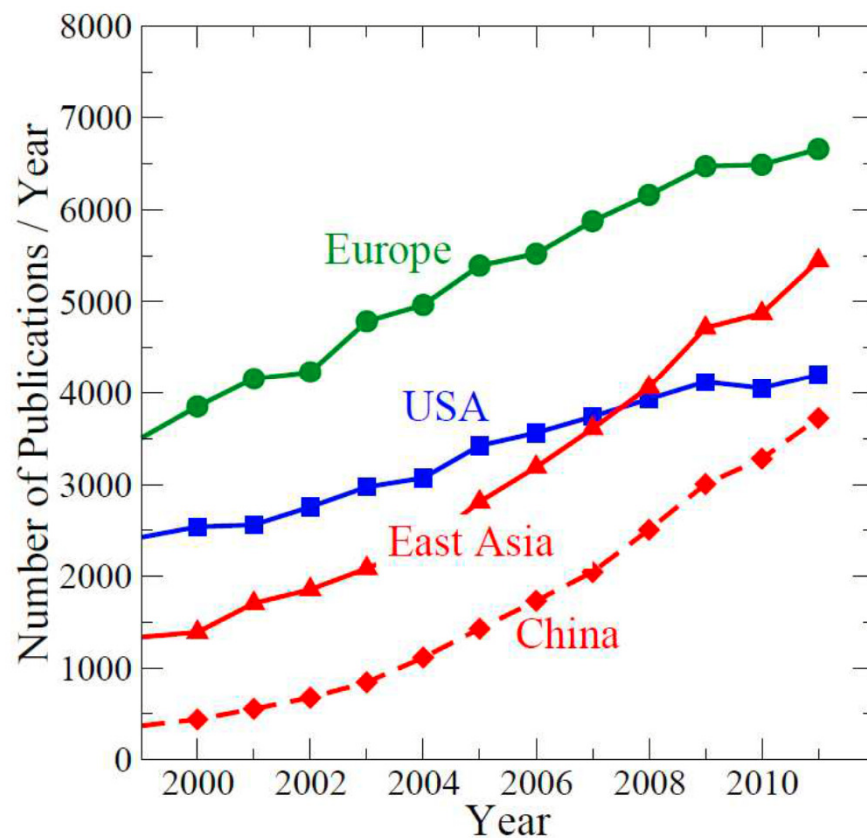
Denmark	27
Germany	21
United States	19
China	15
Italy	11
South Korea	9
India	9
United Kingdom	7
Sweden	5
Russia	3

Europe 56%
Male 80 %

World activity in DFT in terms of publications

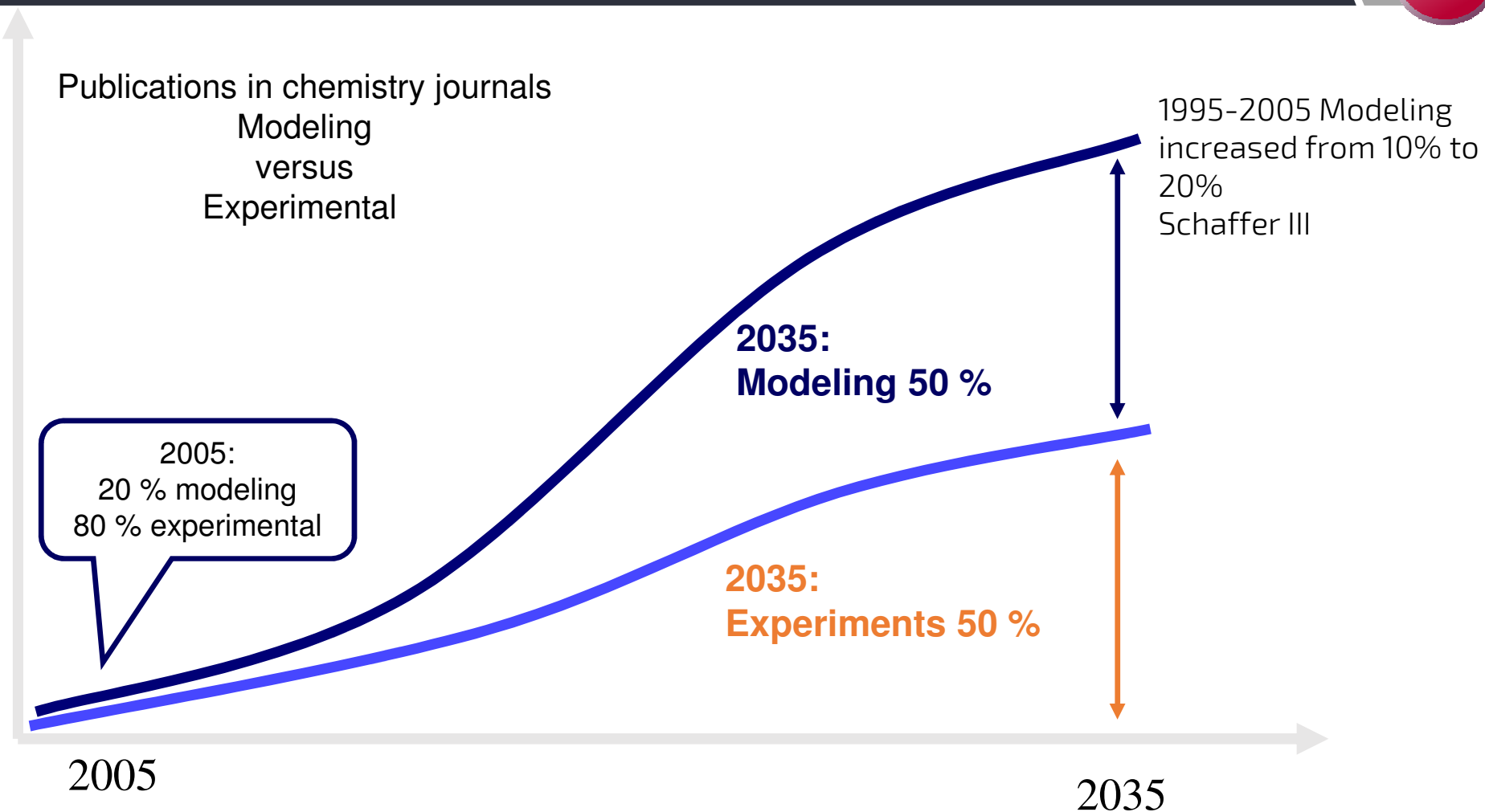


Publications in DFT per year (1999-2011)



Source: Peter H Dederichs and Phivos Mavropoulos, Forschungszentrum Jülich.

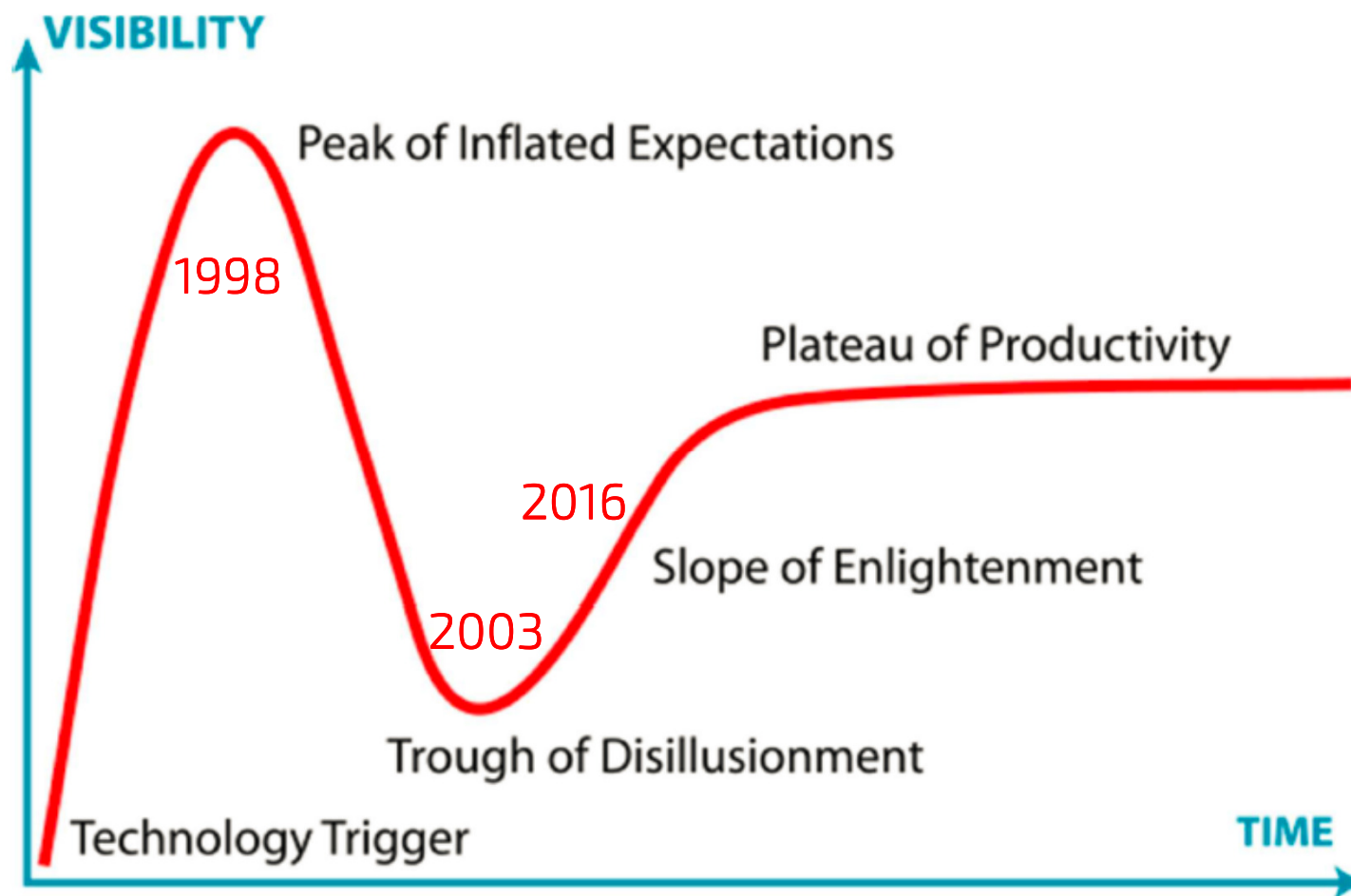
The use of modeling software tools is increasing rapidly





- **Chemical** – major chemical companies have modeling groups since the 1980's using discrete models; modelling of solid state systems (heterogeneous catalysis) started later; smaller chemical companies are still in the process of adopting discrete models
- **Electronic** – leading electronics companies have been pioneering discrete models on the electronic and atomistic levels since the 1970's (IBM, NEC, Bell Labs); today major players like Intel, Samsung, Fujitsu, Panasonic, TSMC use commercial e/a software
- **Automotive** – leading companies like Toyota, Honda, GM have been using e/a modelling in-house since several decades; European car companies are in the process of adopting e/a modelling
- **Oil, gas, energy** – leading companies like Shell and ExxonMobil have in-house modelling groups using e/a models; government supported research organizations (IFPEN, Mexian Petroleum Institute) support industrial efforts
- **Other** –

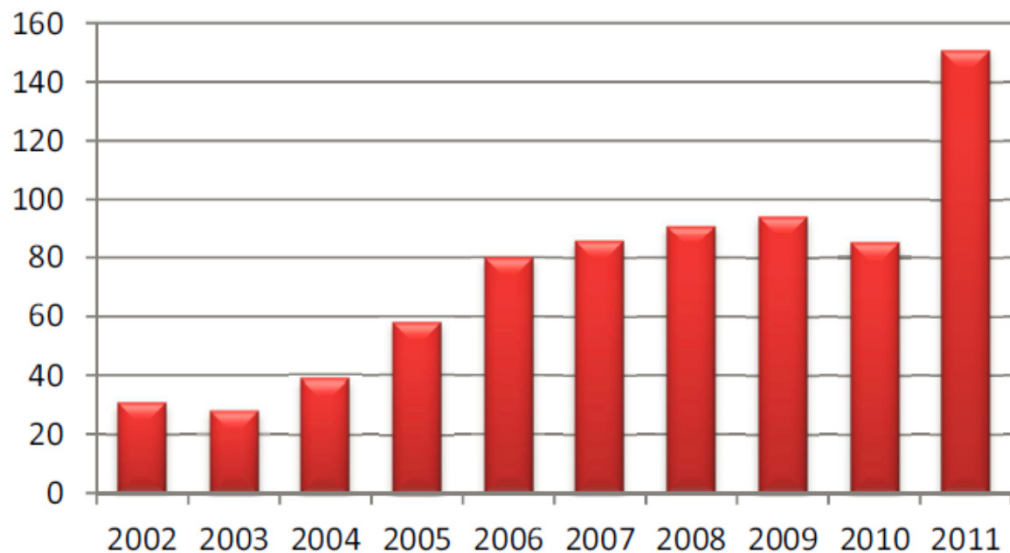
Industrial impact



Patents including the term DFT



"Density Functional" Patents



Application areas

IPC	Description	Percentage
H01	Basic electric elements	26%
C07	Organic chemistry	21%
C ...	Other areas of chemistry	24%
B01	Physical or chemical processes	10%
A	Health, Medical	6%
G06	Computing, Calculating, Counting	5%

Sample Atomistic and Continuum Modelling Software



	Atomistic		Continuum	
	Academic-Gov	Commercial	Academic-Gov	Commerical
Simulation Engines	VASP (EU) CASTEP (EU) Quantum Espresso (EU) Wien2k (EU) SIESTA (EU) FHI-aims (EU) Abinit (EU) Turbomole (EU) GPAW (EU) MOPAC (US) NWChem (US) Lammmps(US) Gulp (US)	ATK (EU) ADF (EU) DMOL (EU) Gaussian (US) Jaguar (US)	OpenFoam Agros2D CalculiX Deal.II DUNE Elmer FEATFLOW FEATool FEAP FEB OOF (USA)	Ansys (US) Abaqus (EU) COMSOL (EU/US) ADINA Advance Design Setaurus LS-Dyna Nastran VisualFEA (AP)
Front ends	ASE (EU) PYMATGEN (US) PyMD VMD Molden	VNL-ATK (EU) Materials Studio (EU) ADF-GUI (EU) MAPS (EU) Schrodinger (US) Gaussview (US) Culgi (EU) MEDEA (EU/US)	Paraview/VTK	Ansys (US) Abaqus (EU) COMSOL (EU/US) Setaurus workbench (US) Simscale VisualFEA (AP) Granta (EU)

<http://asdn.net/asdn/links/software.php#design>

https://en.wikipedia.org/wiki/List_of_finite_element_software_packages

Commercial modelling companies



Employees	Atomistic	Continuum
<20	Scienomics (EU) Culgi (EU) Gaussian (US) SCM (EU)	Intuition software (AP)
20-100	Materials Design (EU/US) QuantumWise (EU) Schrodinger (US) Tripos (US)	Granta (EU)
100<	Dassault systems (EU)	Ansys (US) Comsol (EU/US) Synopsys (US) Dassault systems (EU)

Outline



QuantumWise

Atomic-scale modelling in the semiconductor industry

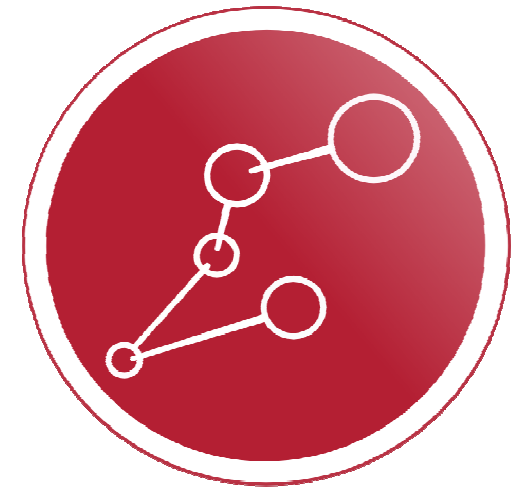
Application example: Interfaces

Concluding remarks

Company background

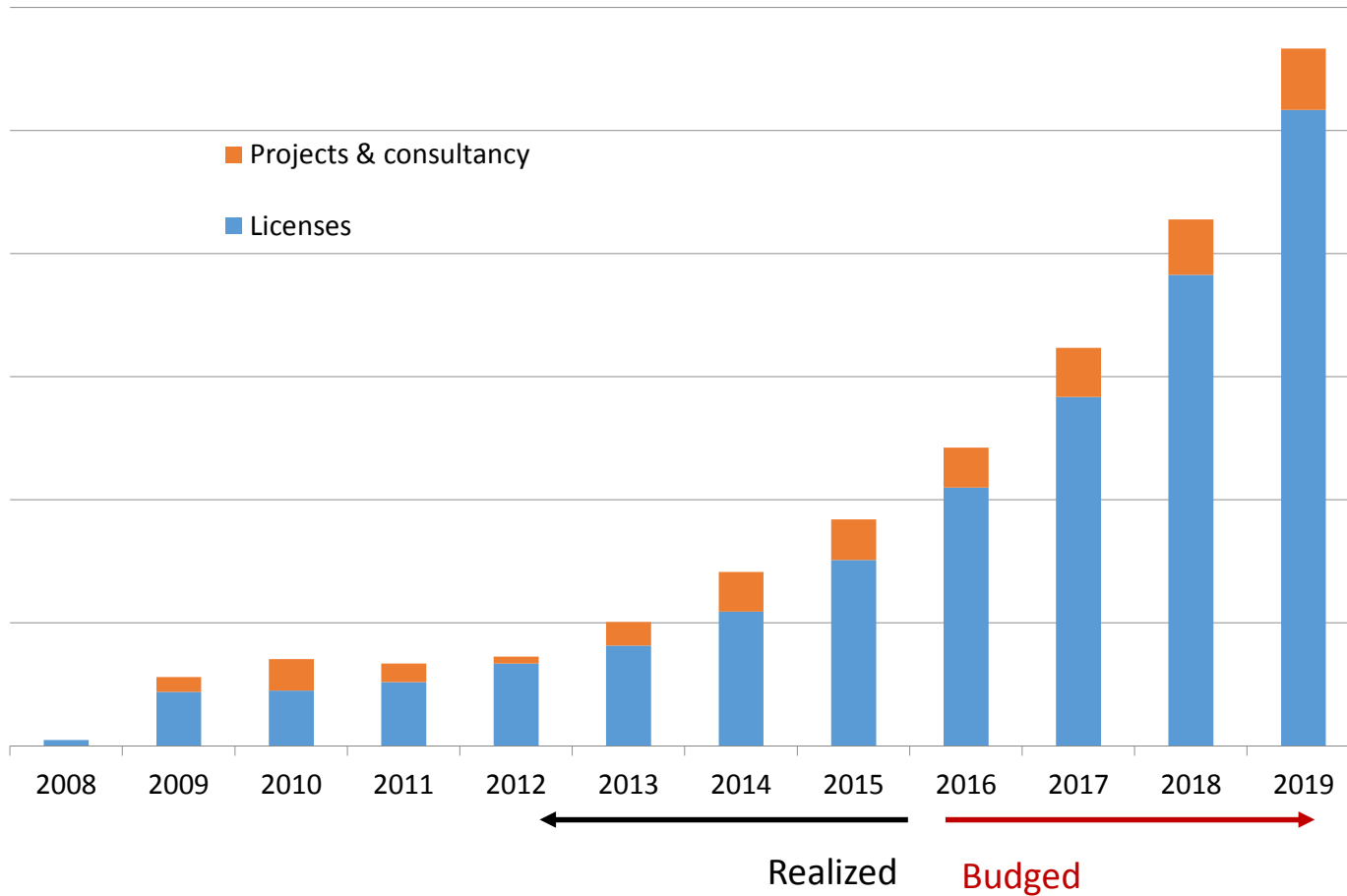
- We love science/physics - and in particular atomic scale simulations
- Help customers be more successful in atomic-scale modelling
- Internal development of quantum-mechanical simulation engines combined with community codes in certain areas
- Founded 2008, with Headquarter in Copenhagen, Denmark
- 30 FTEs; majority has a PhD (+3-5/year)
- Sales reps in USA, Singapore, Japan
- Resellers in India, China, Taiwan, Korea, ...
- Profitable with 30% growth rate – no external capital

QuantumWise



- More than 300 users worldwide
- Rapidly expanding number of academic and industrial users

Revenue history and projections





Nano-device simulator

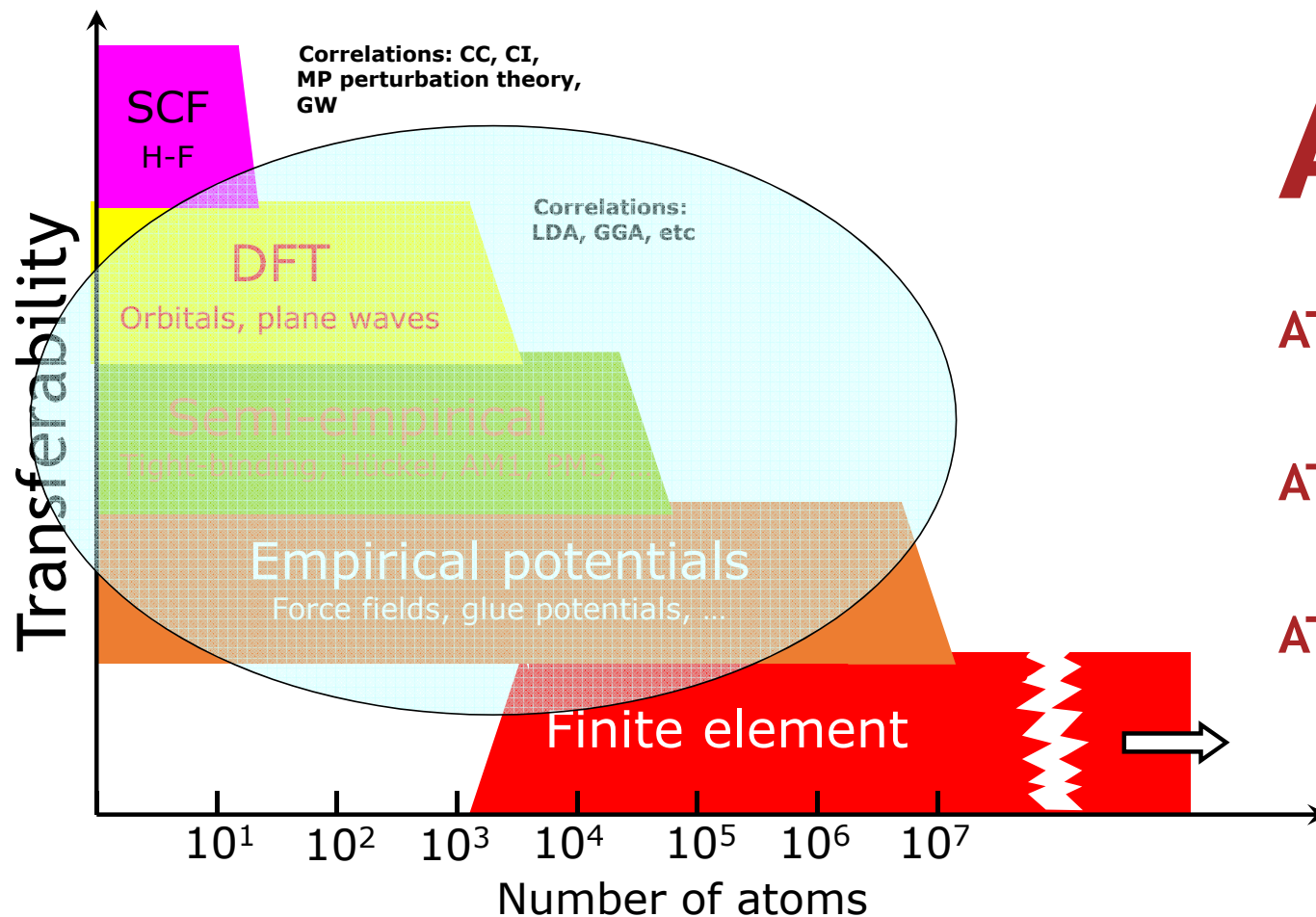
Nano-device simulator with unique functionality, based on atomic-scale modeling, which can replace/complement current TCAD device simulators that use a continuum description

- Simulation of semiconductor, magnetic and interface systems
- Other emerging devices, molecular electronics, organic crystals

Atomic-scale modeling platform

Professional platform which integrates multiple atomic-scale modeling techniques, that can accelerate R&D within materials and electronics in multiple industry sectors

- Fast and accurate DFT calculations + semiempirical models
- Interface to other simulation engines (like VASP, Abinit, FHIaims, QuantumEspresso, GPAW, SIESTA, Wien2k)
- Industry-quality classical MD engine
- Calculation of parameters for TCAD tools



ATK

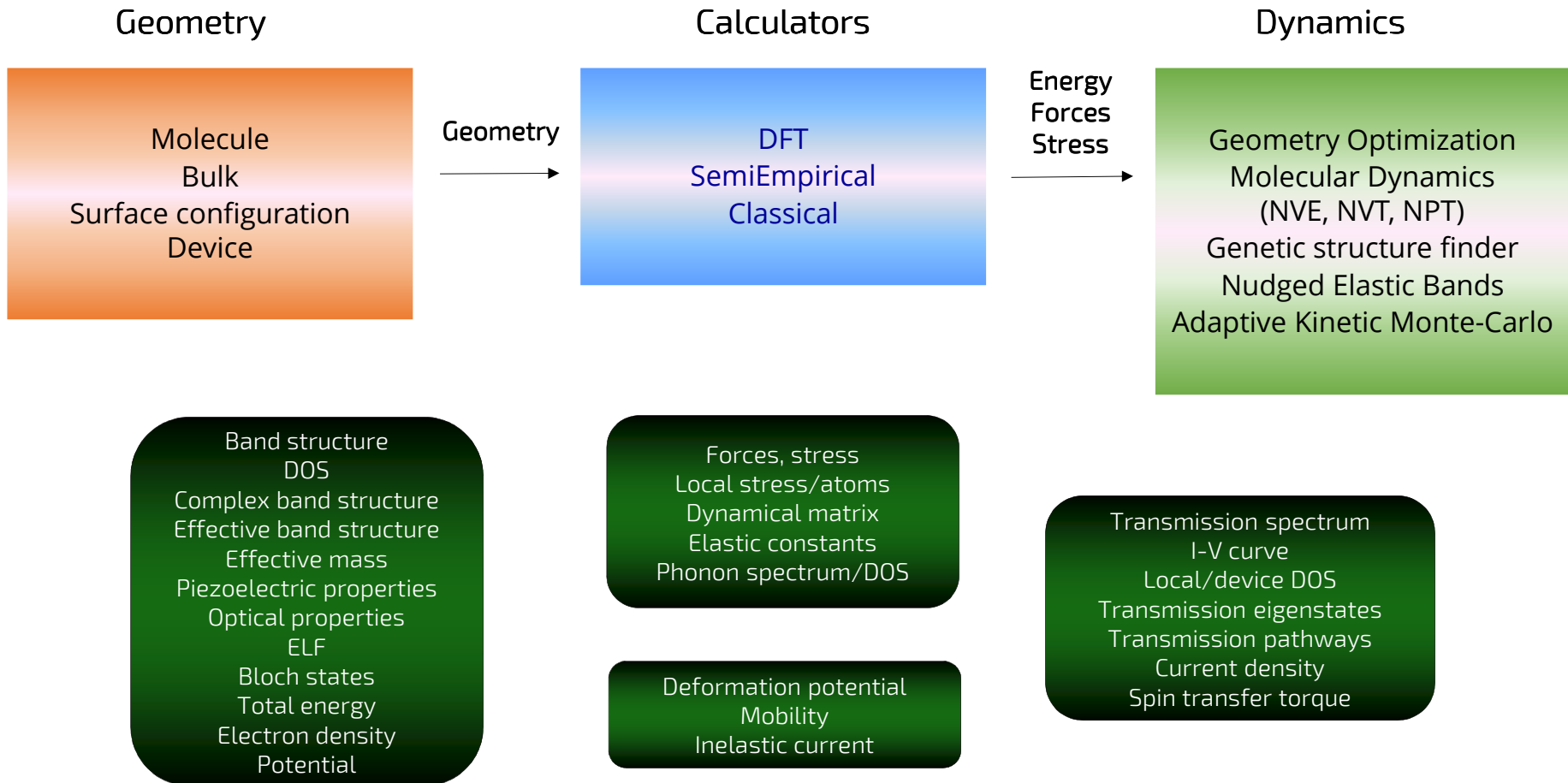
FHI-aims (full potential)
Abinit (Plane Waves)

ATK-DFT (LCAO)

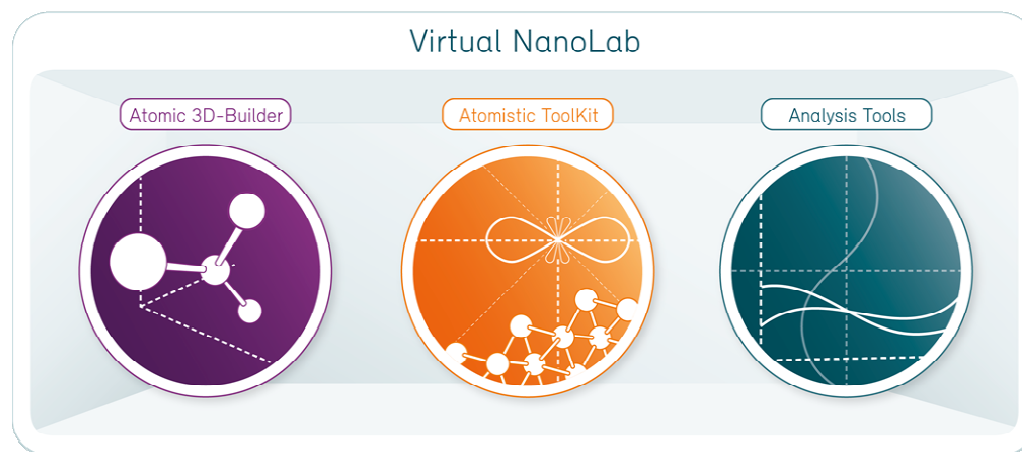
ATK-SE

ATK-Classical

Python interface to atomic-scale simulations



Virtual NanoLab with the Atomistix ToolKit (ATK)



Build

Interfaces
Nanotubes
Nanosheets
Nanopribbons
Molecules
Crystals by symmetry
Cleave surfaces
Polycrystals

Methods

DFT
Semi-Empirical
Classical potentials
(Abinit)
(FHI-Aims)
**Non-Equilibrium Green's Functions
(NEGF) formalism**

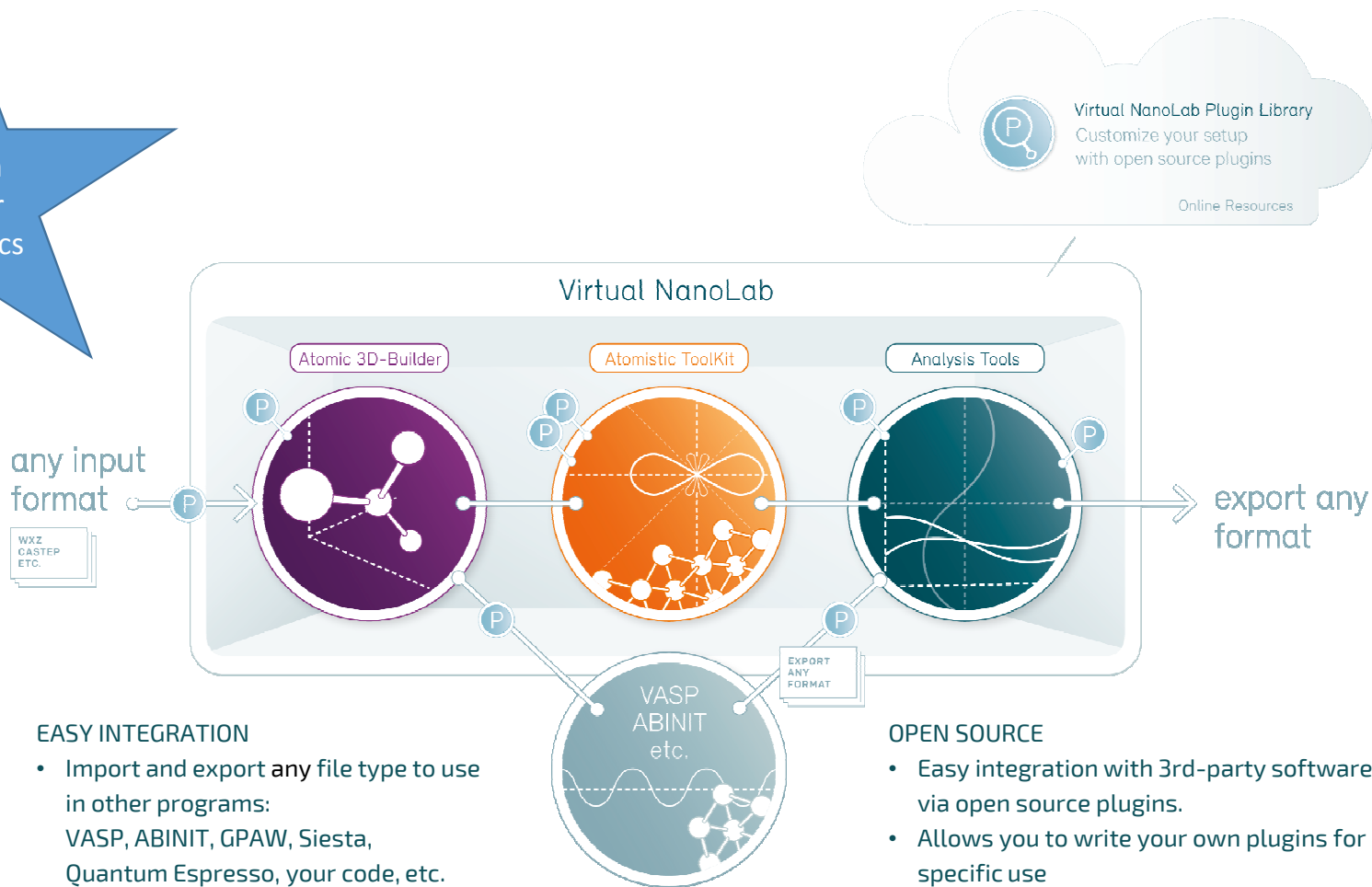
Analyze results

3D visualizations, isosurfaces
Manipulate 3D grids
Band structure, density of states
MD trajectory analysis
Analyze and visualize your data
Produce movies and
animated GIFs

Virtual NanoLab, GUI for ATK and other simulators



Base
version
free for
academics



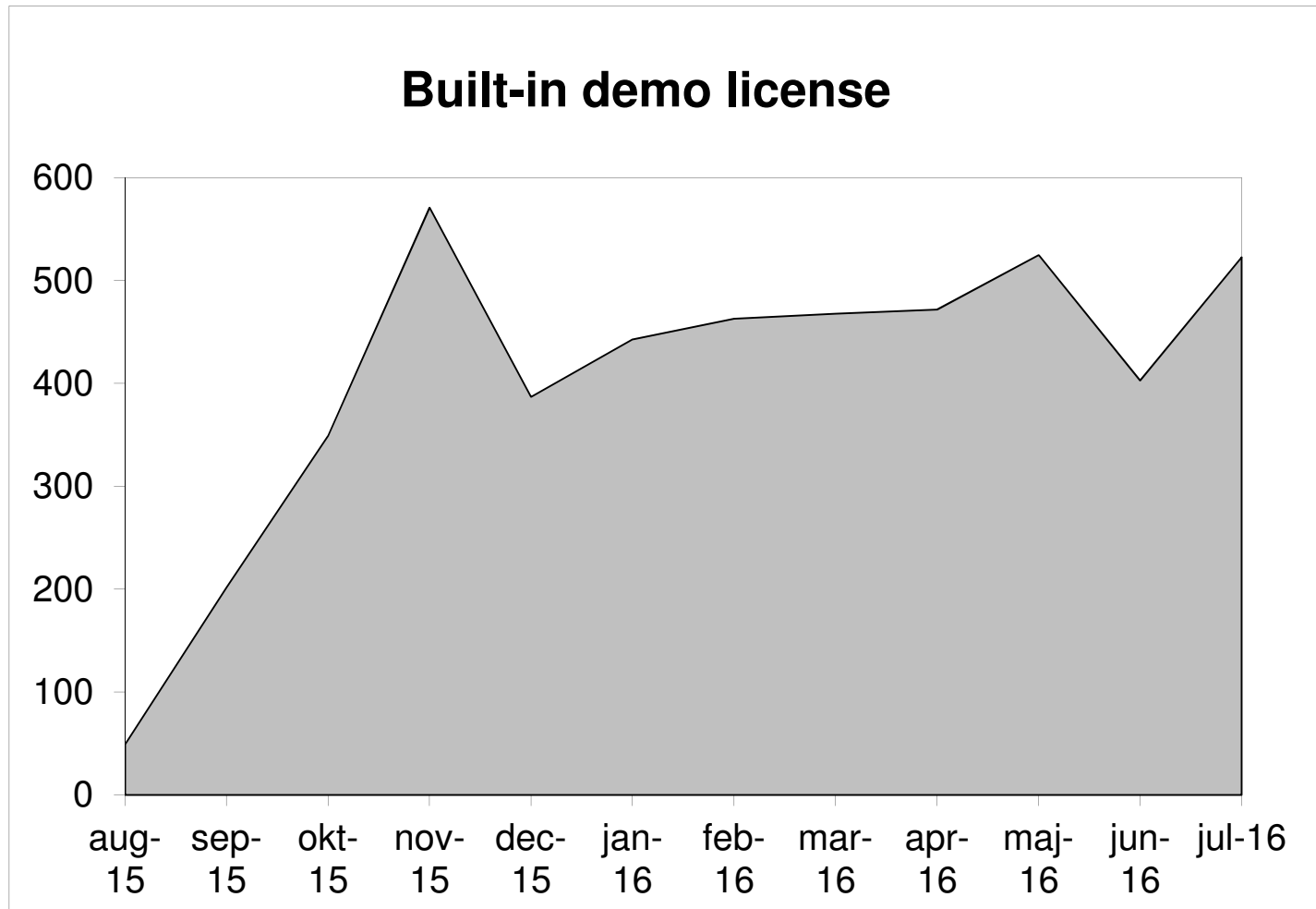
EASY INTEGRATION

- Import and export any file type to use in other programs:
VASP, ABINIT, GPAW, Siesta, Quantum Espresso, your code, etc.

OPEN SOURCE

- Easy integration with 3rd-party software via open source plugins.
- Allows you to write your own plugins for specific use

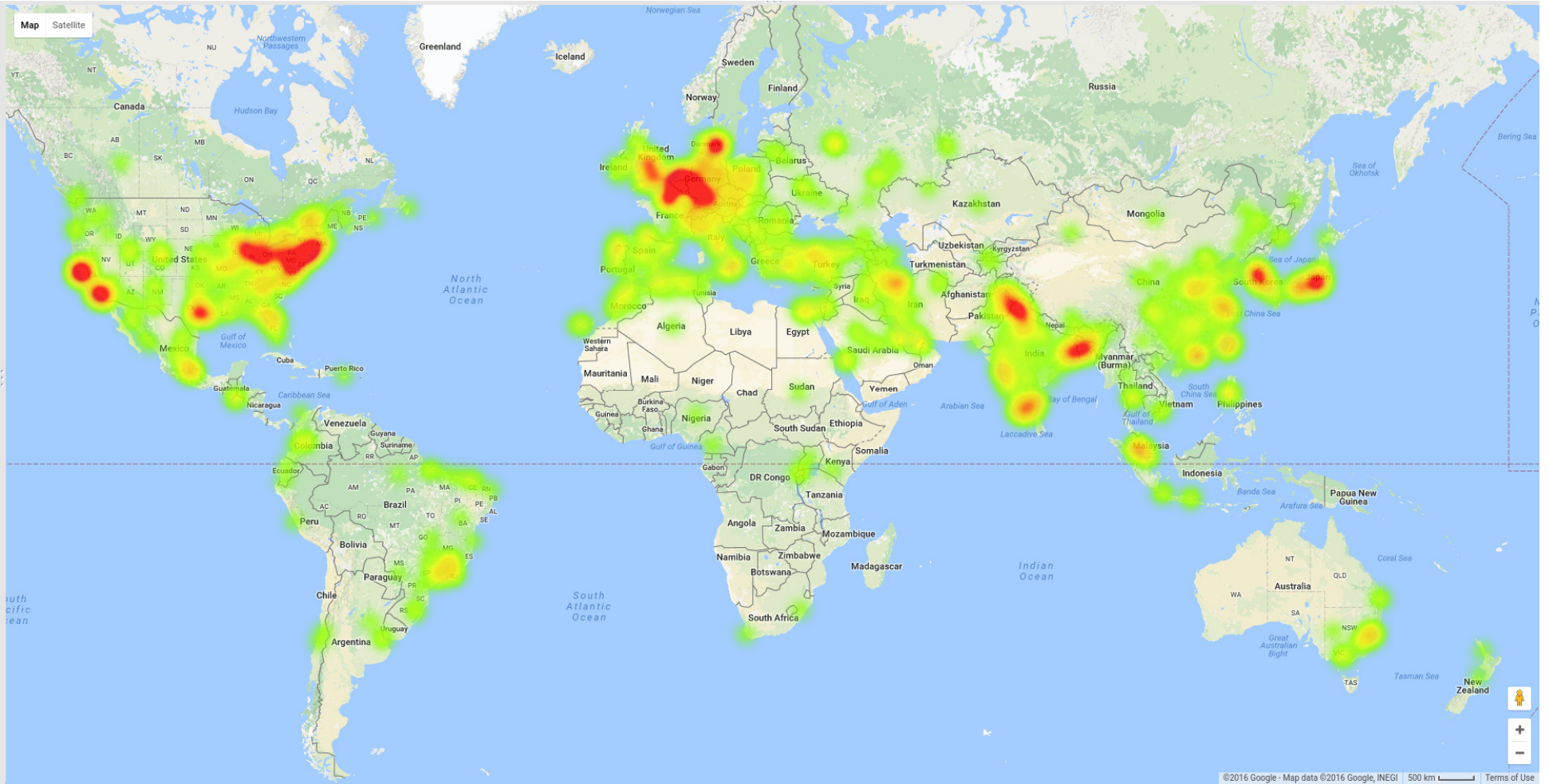
Activation of VNL/ATK license



World users



World users



Free VNL users

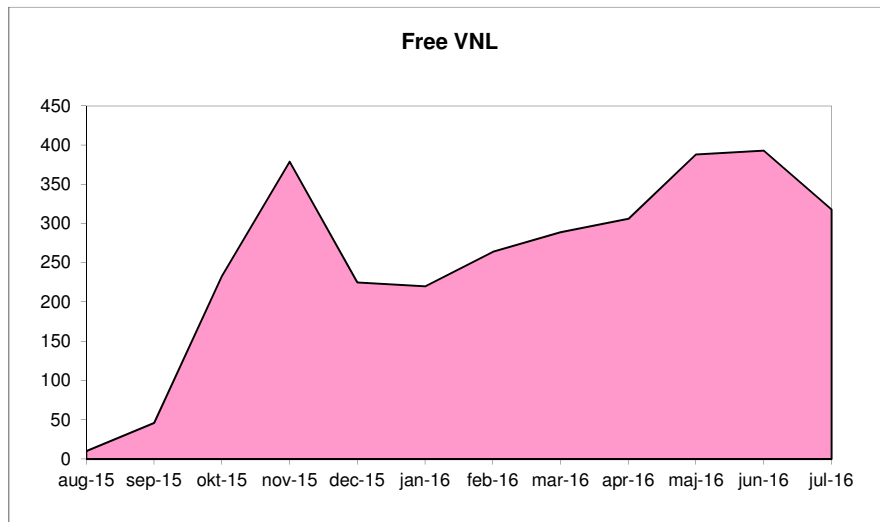


Total licenses sent: 3307
Unique users: 2568
(each account can request up to three licenses)

From 90 different countries

Top 10 countries:

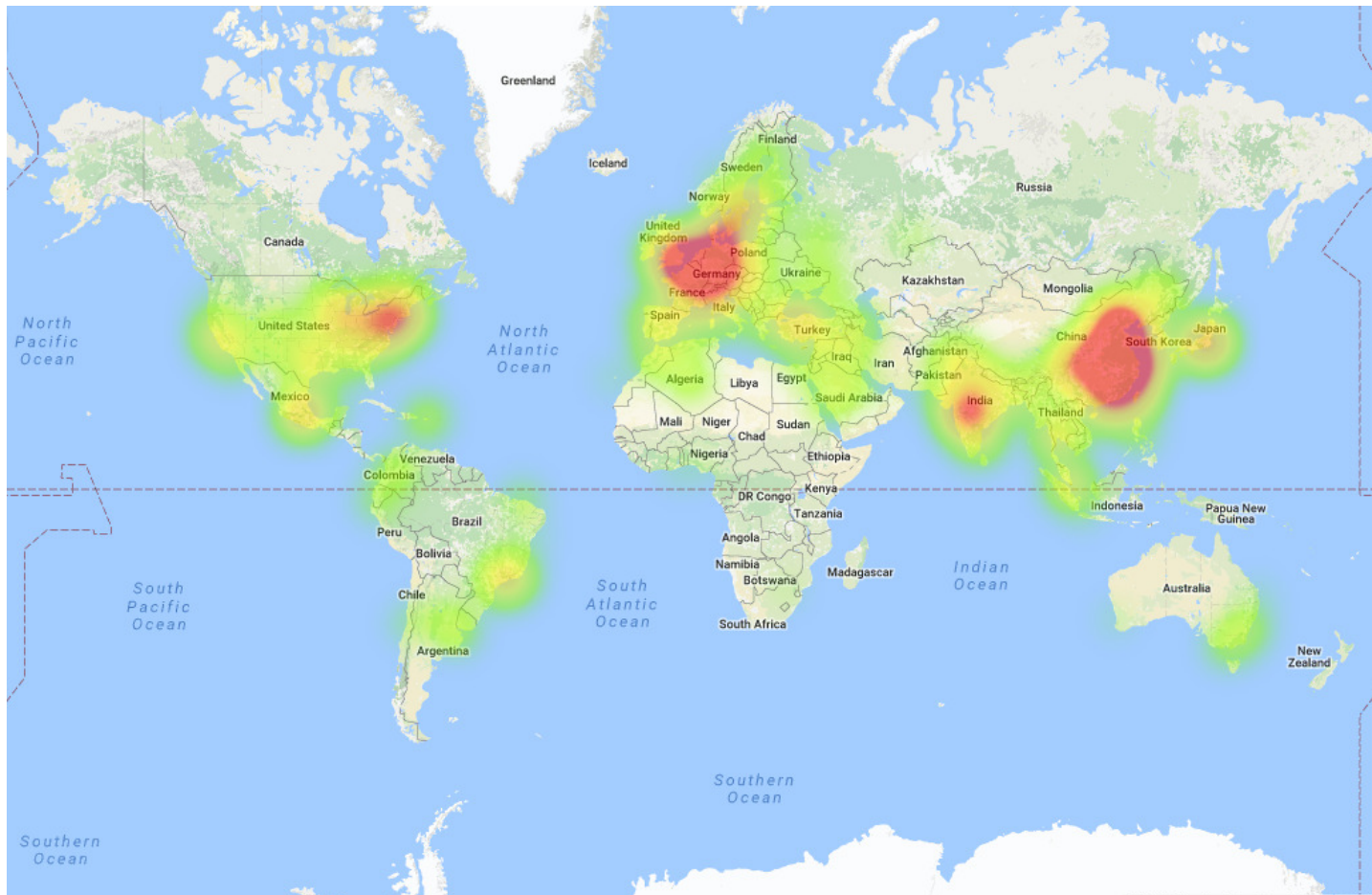
- 705 China
- 536 United States
- 373 India
- 122 Germany
- 112 Japan
- 108 Brazil
- 97 United Kingdom
- 81 Korea
- 79 Mexico
- 60 Spain



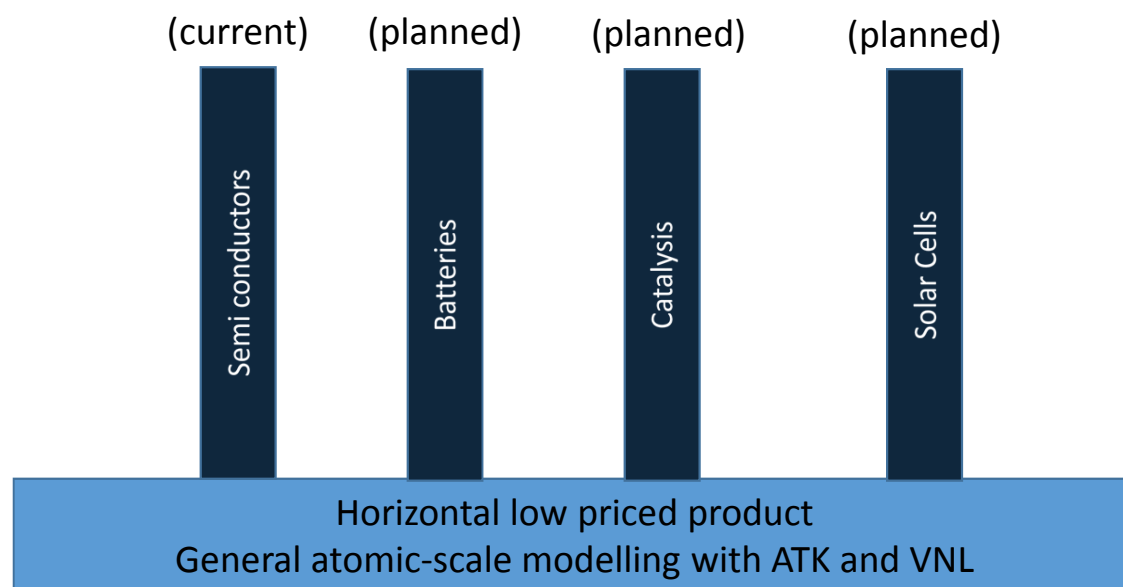
Map of free VNL users



Map of free VNL users



Overall product strategy



Outline

QuantumWise

Atomic-scale modelling in the semiconductor industry

Application example: Interfaces

Concluding remarks

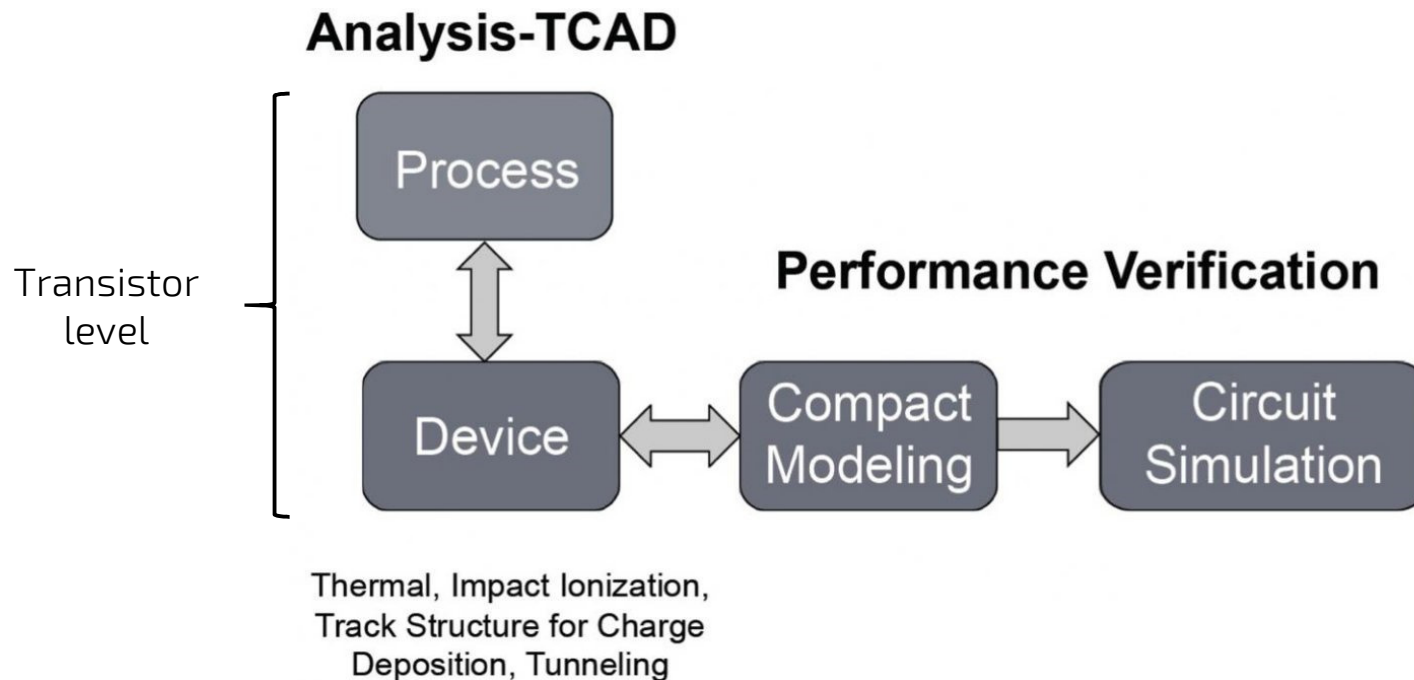


Atomic-scale modelling in the semiconductor industry



Simulation an integral part of the semiconductor industry

The simulation software is develop by the Electronic Design Automation (EDA) software industry

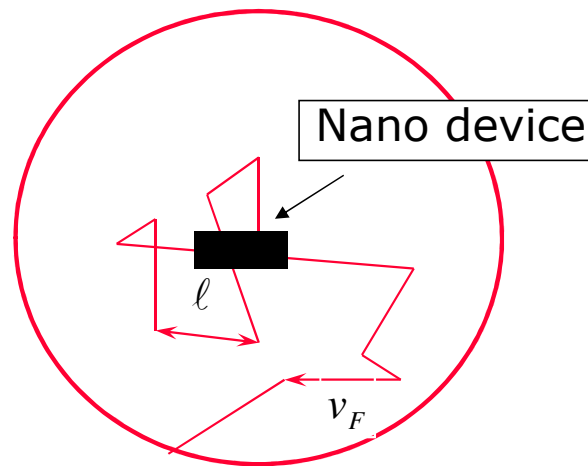




Current TCAD tools use drift-diffusion

Electrons move around randomly
with some average velocity

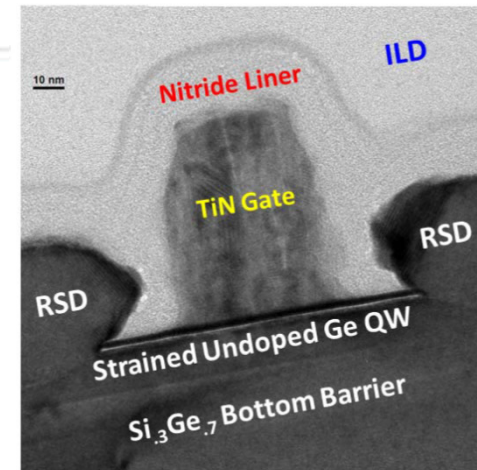
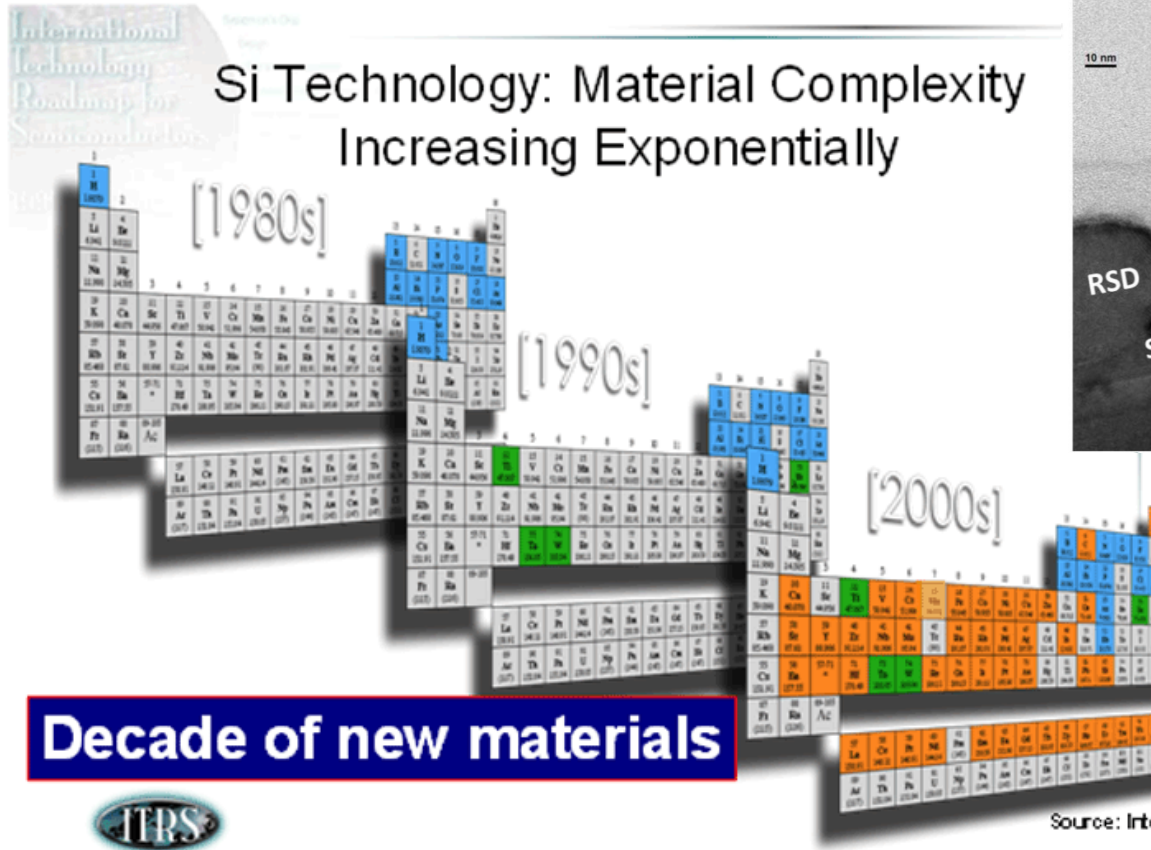
$$v_F = \langle \vec{v}_0 \rangle$$



*This picture breaks down when the
device dimensions are smaller
than the mean free path ℓ*

Furthermore, difficult to generate parameters for the simulation models

Nano means new materials



Ge p-channel quantum well field-effect transistor (QWFET) presented by Intel at IEDM 2010



1. Calculate materials parameters that can be part of multi-scale workflow
 - ❖ Defect formation energies, diffusion lengths
 - ❖ band structure of confined systems
 - ❖ band offsets at interfaces
 - ❖ Emerging devices, graphene, spintronics, ...
2. Perform device modelling at the quantum level for benchmarking continuum level models
 - ❖ FINFET's
 - ❖ p-i-n junctions

Outline

QuantumWise

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Phys. Status Solidi B 247, No. 7, 1791–1796 (2010) / DOI 10.1002/pssb.201046133



Simulation of grain boundary effects on electronic transport in metals, and detailed causes of scattering

Baruch Feldman^{*.1.2.4}, Seongjun Park¹, Michael Haverty¹, Sadasivan Shankar¹, and Scott T. Dunham^{2.3}

¹Process Technology Modeling, Design and Technology Solutions, Technology and Manufacturing Group, Intel Corporation, Santa Clara, CA 95052, USA

²Department of Physics, University of Washington, Seattle, WA 98195, USA

³Department of Electrical Engineering, University of Washington, Seattle, WA 98195, USA

⁴Current address: Tyndall National Institute, University College Cork, Cork, Ireland

Simulation of metal-semiconductor interface

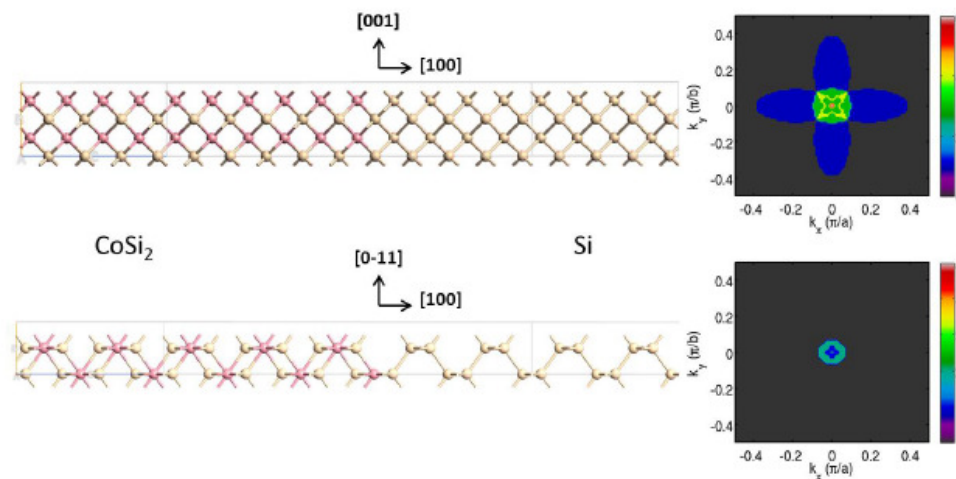


Arxiv:1405.1317v1 [cond-
mat.mtrl-sci]

Effect of realistic metal electronic structure on the lower limit of contact resistivity
of epitaxial metal-semiconductor contacts

Ganesh Hegde^{1, a)} and R. Chris Bowen¹

Advanced Logic Lab, Samsung Semiconductor R&D Center, Austin,



"Valley filtering"



PHYSICAL REVIEW B 93, 155302 (2016)

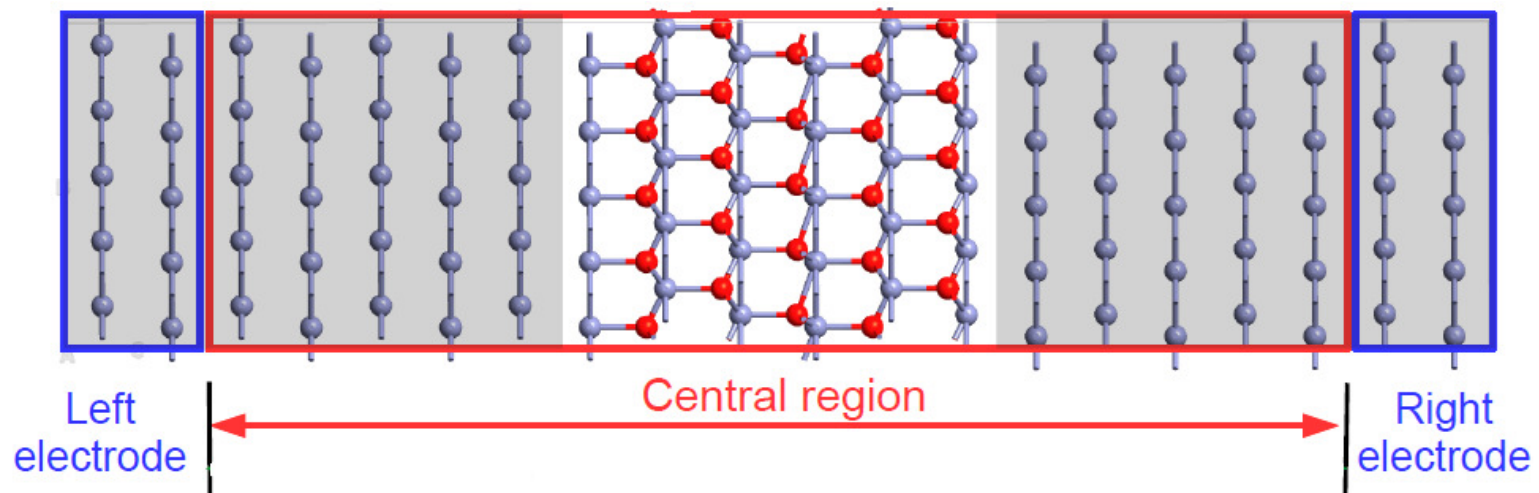
General atomistic approach for modeling metal-semiconductor interfaces using density functional theory and nonequilibrium Green's function

Daniele Stradi,^{1,2,*} Umberto Martinez,² Anders Blom,² Mads Brandbyge,¹ and Kurt Stokbro²
¹*Center for Nanostructured Graphene (CNG), Department of Micro- and Nanotechnology (DTU Nanotech), Ørsteds Plads, Building 345B, DK-2800 Kongens Lyngby, Denmark*
²*QuantumWise A/S, Fruebjergvej 3, Postbox 4, DK-2100 Copenhagen, Denmark*
(Received 18 January 2016; published 7 April 2016)

Metal-semiconductor contacts are a pillar of modern semiconductor technology. Historically, their microscopic understanding has been hampered by the inability of traditional analytical and numerical methods to fully capture the complex physics governing their operating principles. Here we introduce an atomistic approach based on density functional theory and nonequilibrium Green's function, which includes all the relevant ingredients required to model realistic metal-semiconductor interfaces and allows for a direct comparison between theory and experiments via I - V_{bias} curve simulations. We apply this method to characterize an Ag/Si interface relevant for photovoltaic applications and study the rectifying-to-Ohmic transition as a function of the semiconductor doping. We also demonstrate that the standard “activation energy” method for the analysis of I - V_{bias} data might be inaccurate for nonideal interfaces as it neglects electron tunneling, and that finite-size atomistic models have problems in describing these interfaces in the presence of doping due to a poor representation of space-charge effects. Conversely, the present method deals effectively with both issues, thus representing a valid alternative to conventional procedures for the accurate characterization of metal-semiconductor interfaces.

DOI: [10.1103/PhysRevB.93.155302](https://doi.org/10.1103/PhysRevB.93.155302)

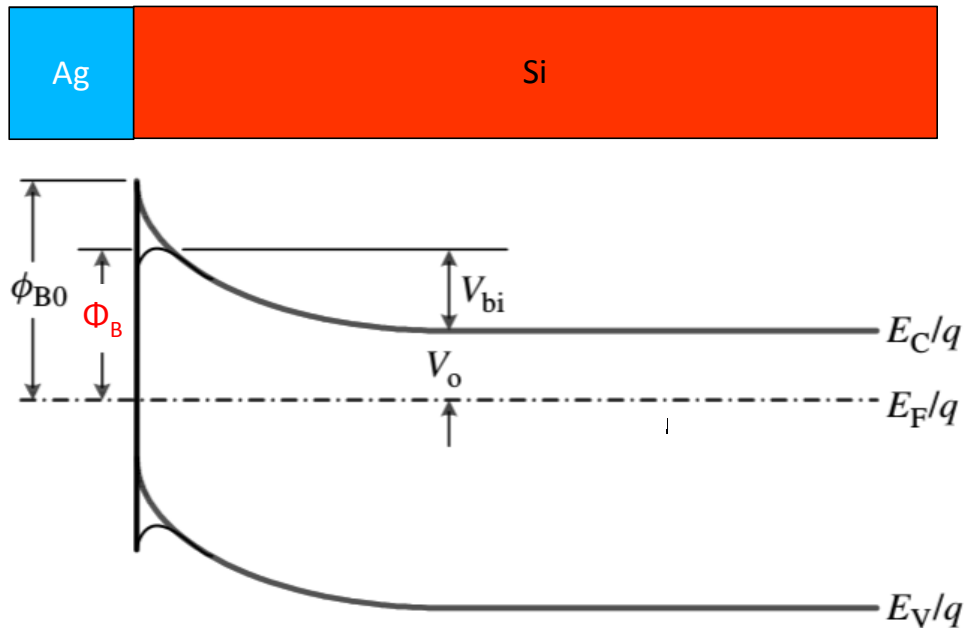
NEGF transport methodology



- ❖ The system is divided into 3 regions: left, central, right regions
- ❖ Properties of left and right regions are calculated using PBC
- ❖ The electron density of the central region is donated by the electrode reservoirs, i.e. open boundary conditions
- ❖ The electro-static potential of the central region is obtained from the density and using the electrode boundary conditions

M. Brandbyge et. al. PRB. 65, 165401 (2002). Stradi et. al. PRB 93, 155302 (2016).

Metal-Semiconductor Schottky contact



Φ_{B0} = Ideal barrier height
 Φ_B = Effective barrier height
 V_{bi} = built in potential
 V_0 = potential ($E_F - E_V$)

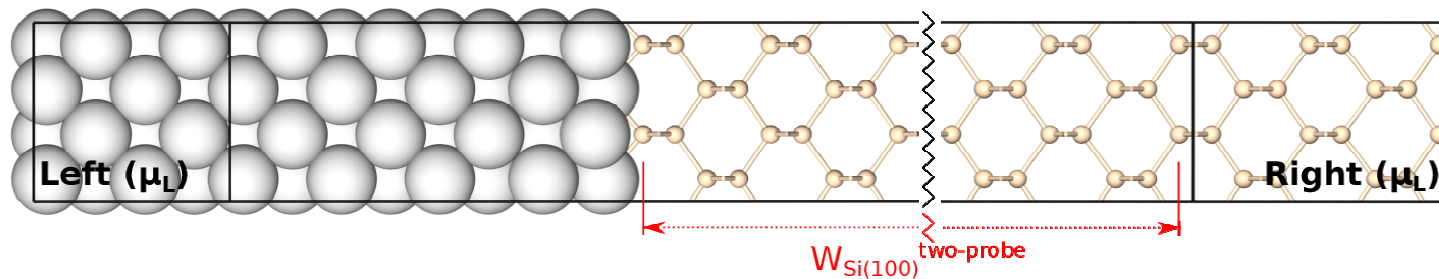
In the thermionic regime the current is described by:

$$I = AA' T^2 e^{-q\Phi_B/k_B T} \left(e^{qV/nk_B T} - 1 \right)$$

I = current
 $A' = 4\pi q k^2 m^*/h^3$ (Richardson constant)
 A = electrically active area
 n = ideality factor

*Sze, Ng *Physics of Semiconductor Interfaces* 3rd ed. Wiley 2007
 Schroeder *Semiconductor Material and Device Characterization* 3rd ed. Wiley 2006

Model Ag(100)/Si(100) investigated using DFT+NEGF



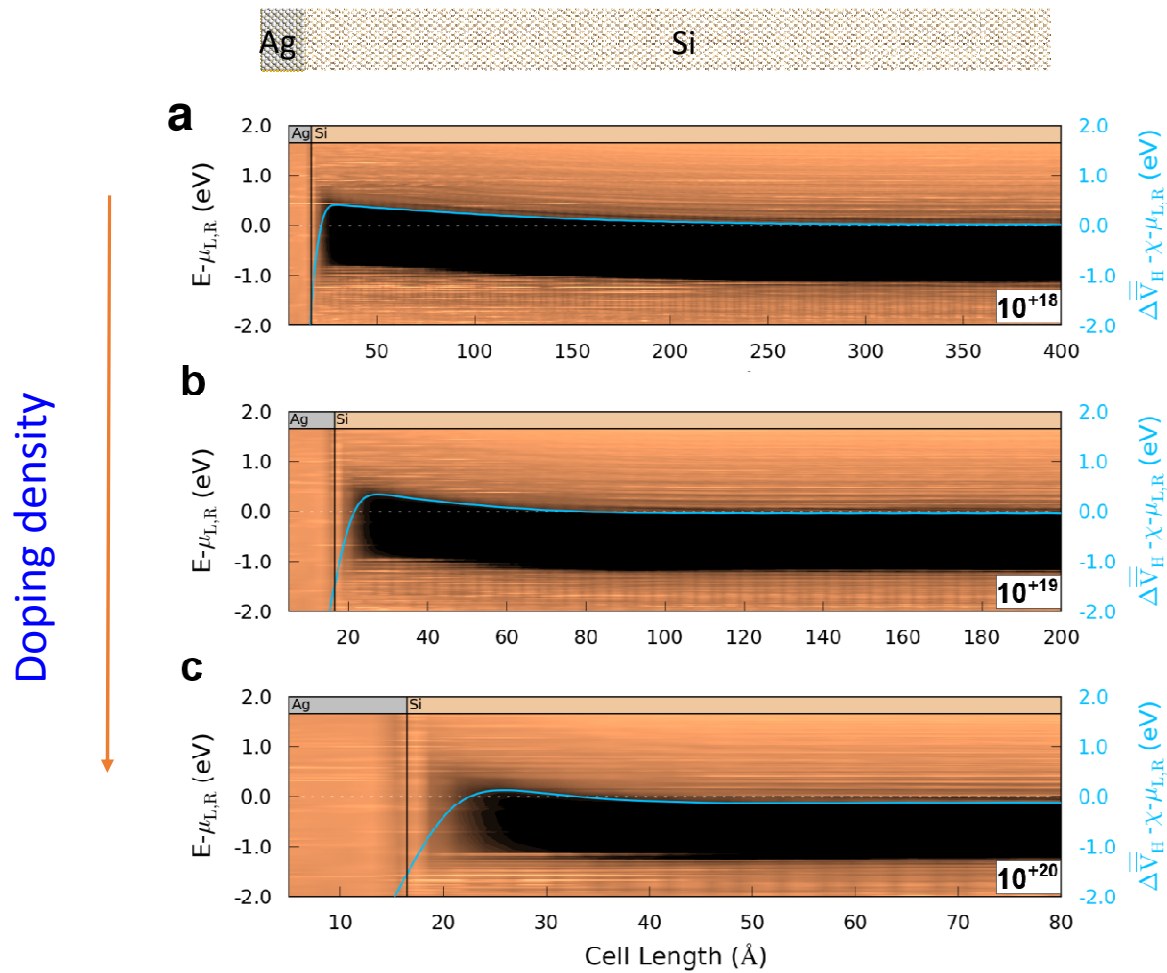
- **DFT+NEGF formalism***: exact representation of the non-periodic interface
- **Meta-GGA functional****: correctly accounts for the silicon band gap ($E_g = 1.17$ eV)
- **Effective doping** of the silicon side using localized charges on the Si atoms

Stradi et. al. *Phys. Rev. B* **93**, 155302 (2016).

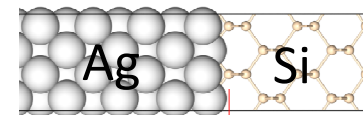
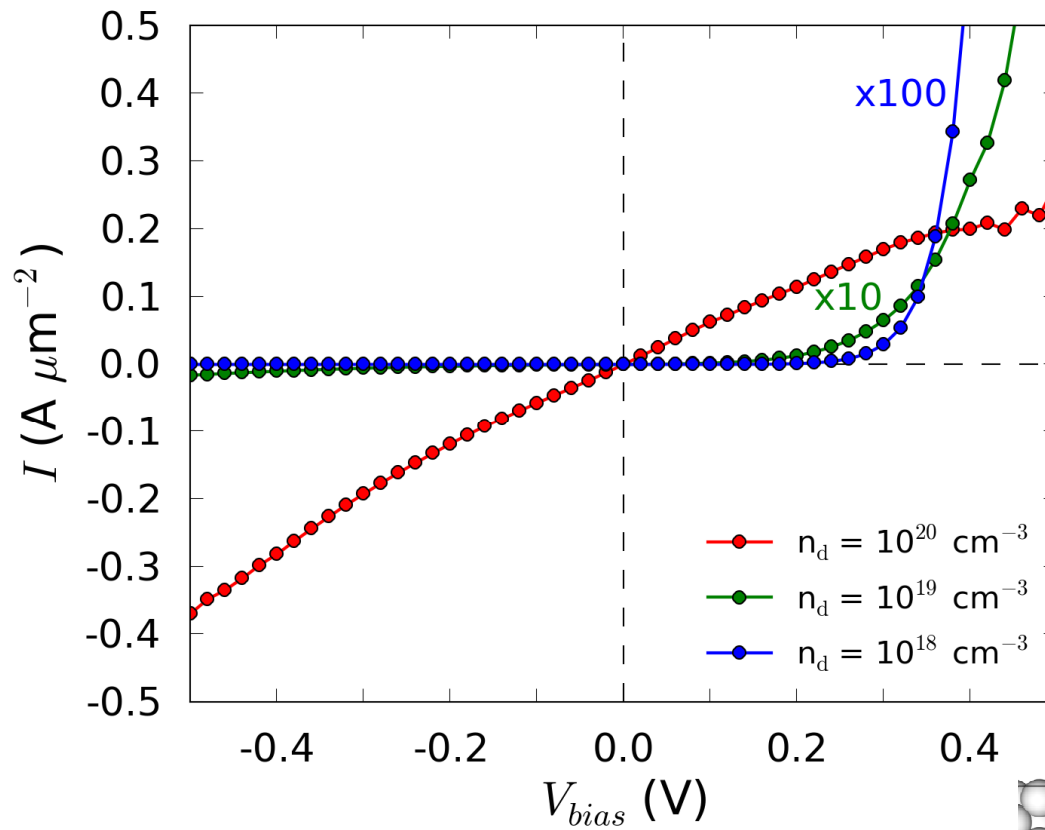
*Brandbyge et al. *Phys. Rev. B* **65**, 165401 (2002)

** Tran, Blaha *Phys. Rev. Lett.* **102**, 226401 (2009)

Band bending as function of doping



Calculated I-V characteristics

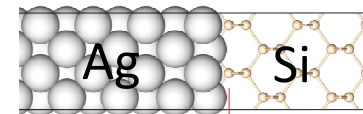
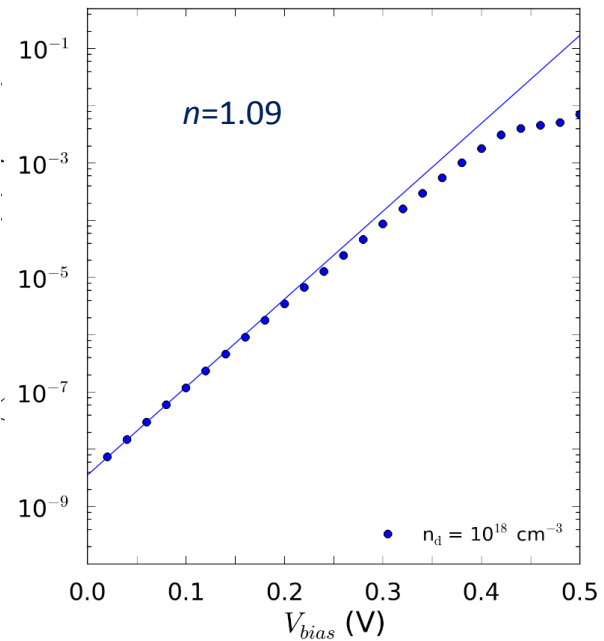
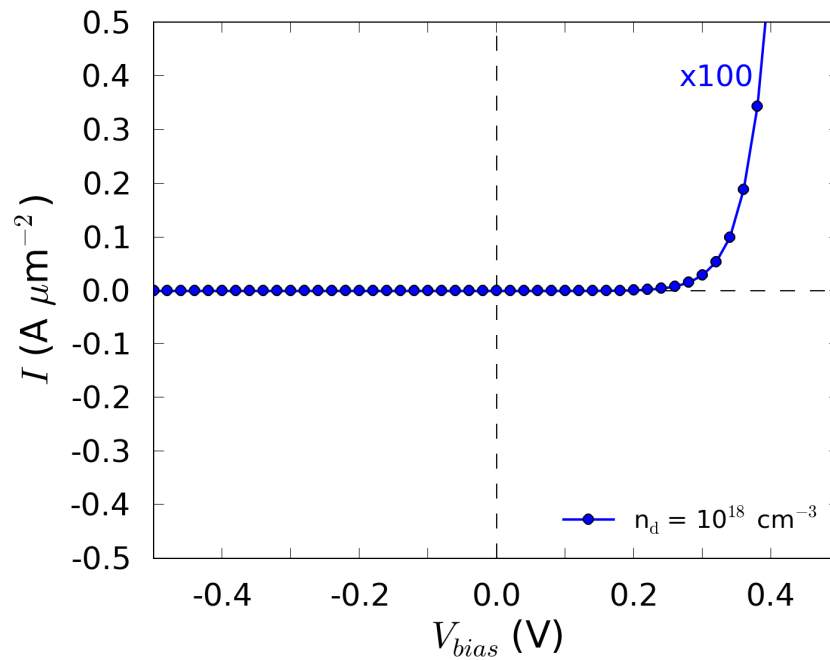




Calculated I-V characteristics and extraction of ideality factor n

$$I = AA' T^2 e^{-q\Phi_B/k_B T} \left(e^{qV/nk_B T} - 1 \right)$$

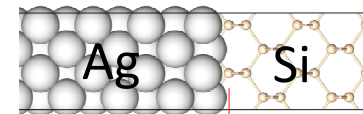
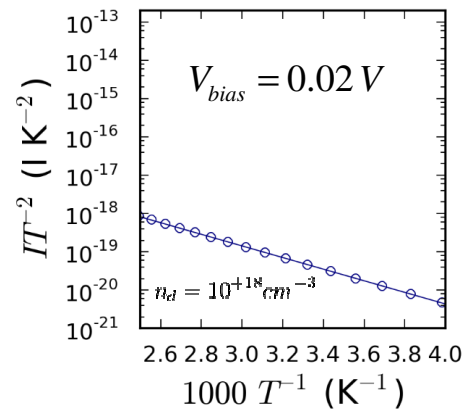
$$I = I_0 \left(e^{qV/nk_B T} - 1 \right)$$





Schottky barrier from temperature dependence

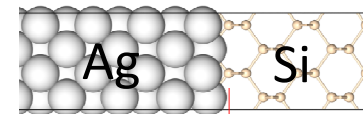
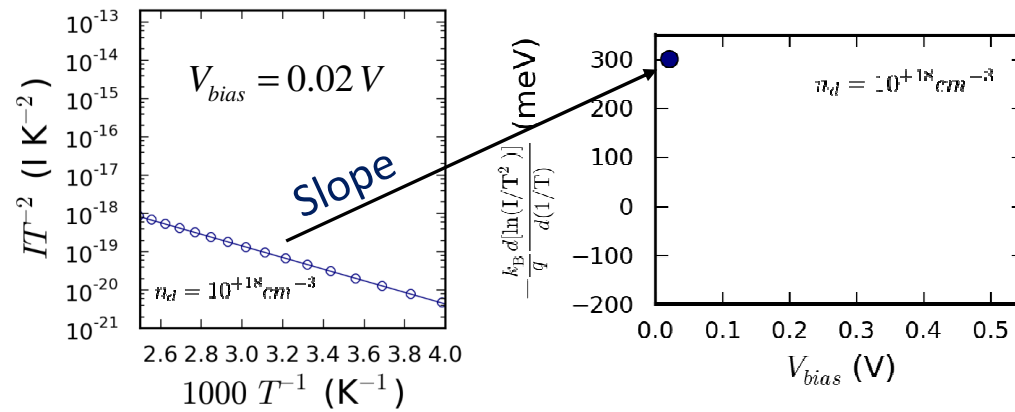
$$I = AA' T^2 e^{-q\Phi_B/k_B T} \left(e^{qV/nk_B T} - 1 \right) \quad \rightarrow \quad -\frac{k_B}{q} \frac{d[\ln(I/T^2)]}{d(1/T)} = \Phi^{AE} - \frac{V_{bias}}{n}$$





Schottky barrier from temperature dependence

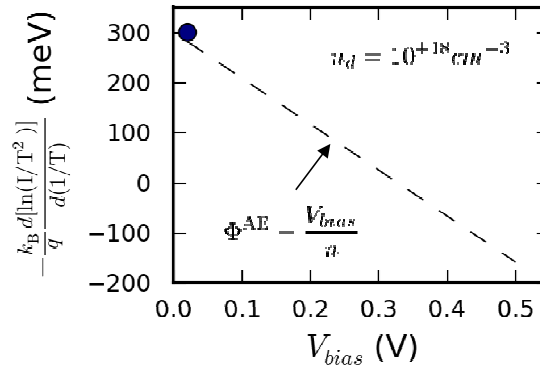
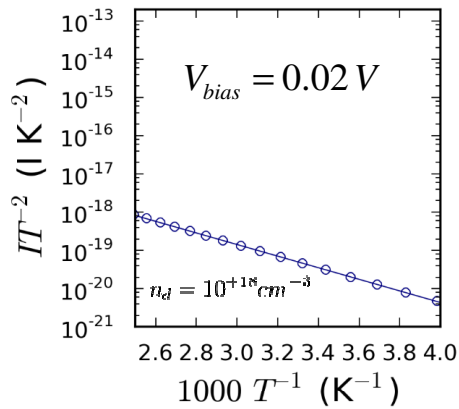
$$I = AA' T^2 e^{-q\Phi_B/k_B T} \left(e^{qV/nk_B T} - 1 \right) \quad \rightarrow \quad -\frac{k_B}{q} \frac{d[\ln(I/T^2)]}{d(1/T)} = \Phi^{AE} - \frac{V_{bias}}{n}$$





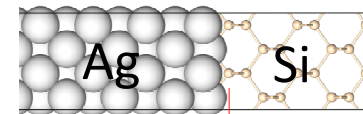
Calculated activation energy curves

$$I = AA' T^2 e^{-q\Phi_B/k_B T} \left(e^{qV/nk_B T} - 1 \right) \rightarrow -\frac{k_B}{q} \frac{d[\ln(I/T^2)]}{d(1/T)} = \Phi^{AE} - \frac{V_{bias}}{n}$$



Bias dependence

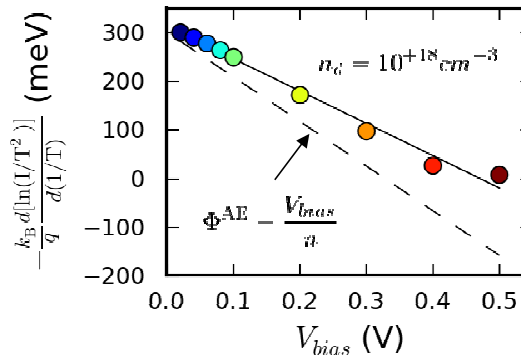
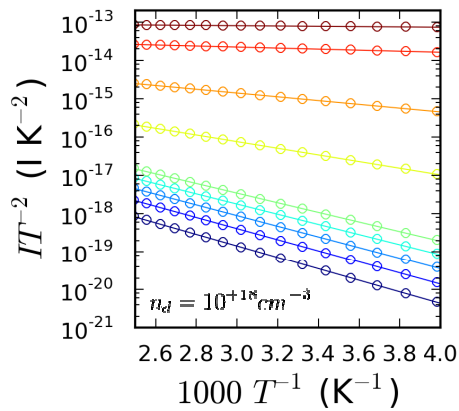
$$\Phi^{AE} - \frac{V_{bias}}{n}$$





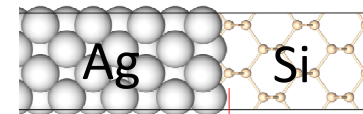
Calculated activation energy curves

$$I = AA' T^2 e^{-q\Phi_B/k_B T} \left(e^{qV/nk_B T} - 1 \right) \quad \rightarrow \quad -\frac{k_B}{q} \frac{d[\ln(I/T^2)]}{d(1/T)} = \Phi^{AE} - \frac{V_{bias}}{n}$$



Bias dependence

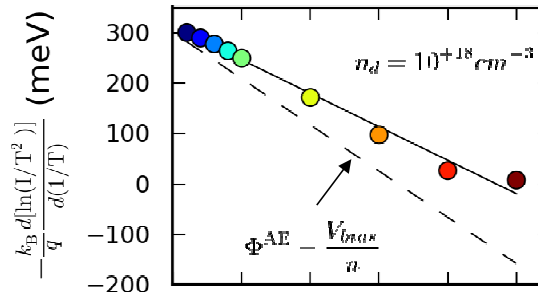
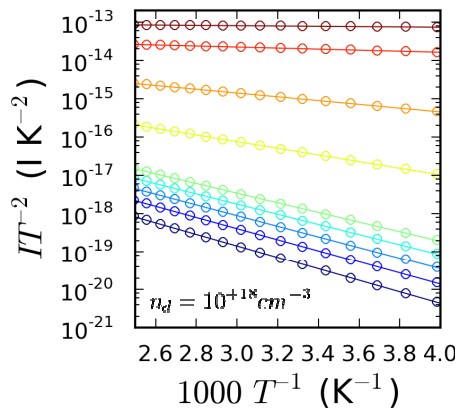
$$\Phi^{AE} - \frac{V_{bias}}{n}$$





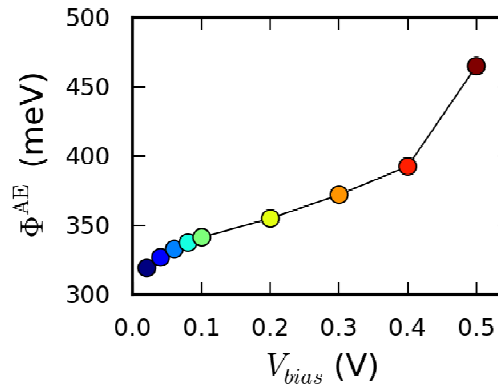
Calculated activation energy curves

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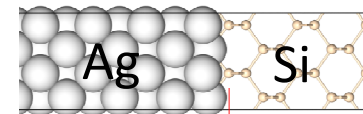
Bias dependence

$$\Phi^{AE} - \frac{V_{bias}}{n}$$

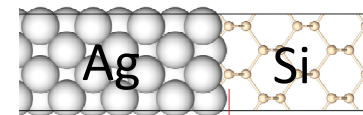
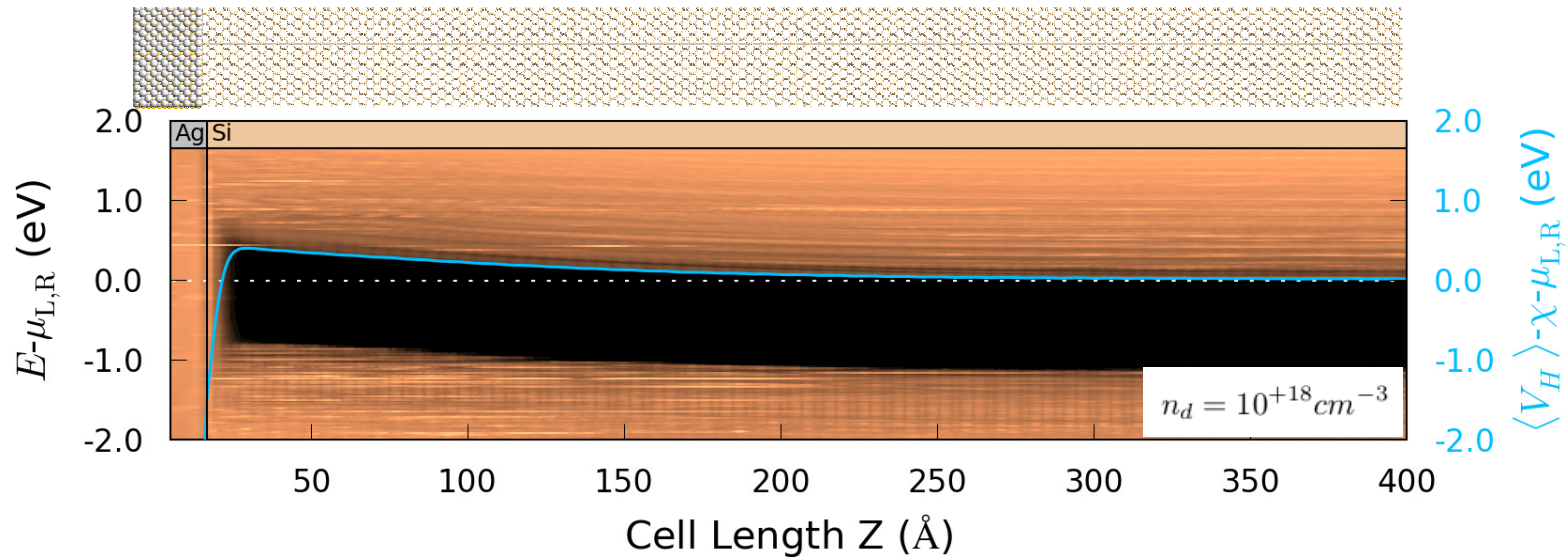


Calculate eff. barrier

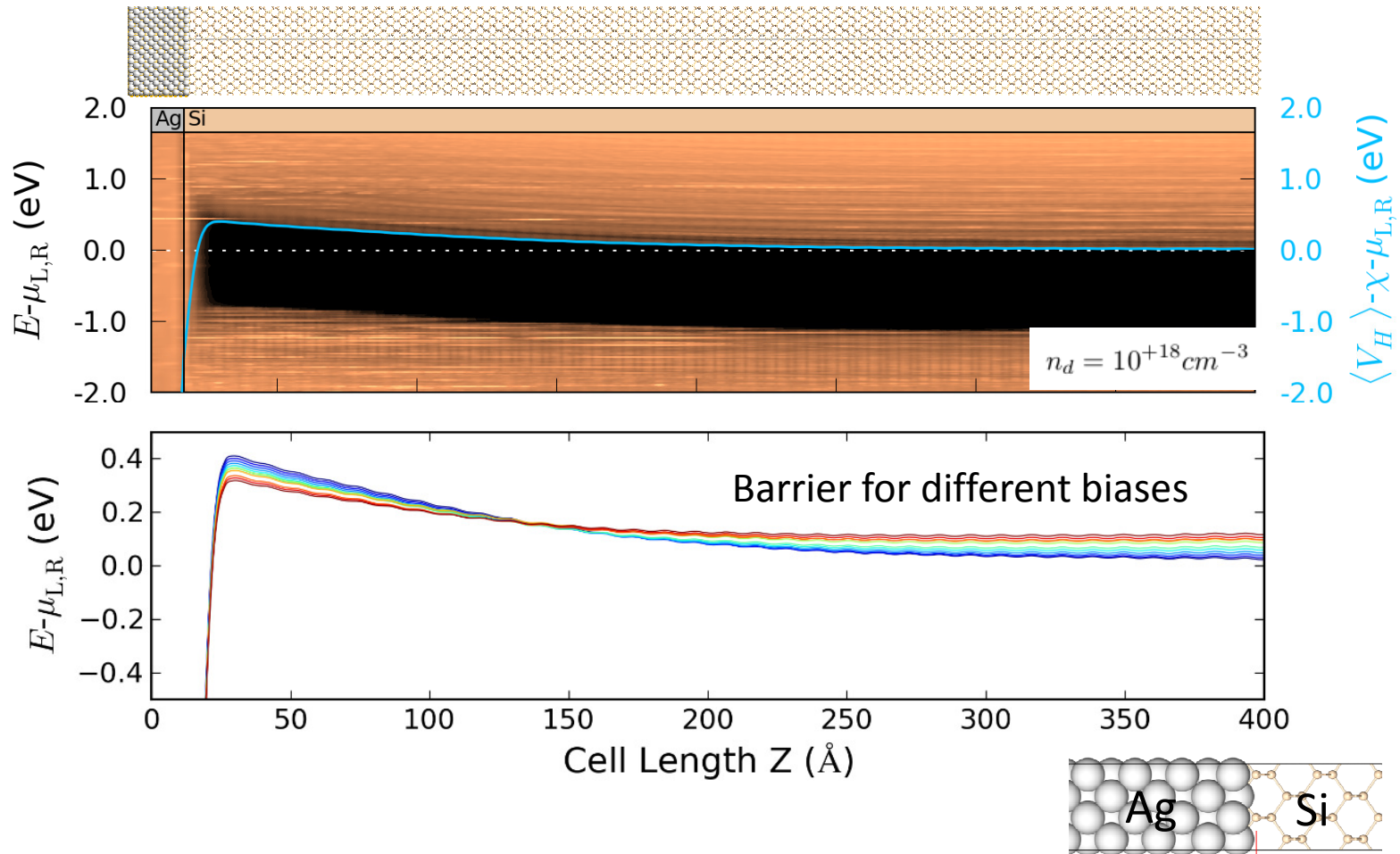
$$\Phi^{AE} = -\frac{k_B}{q} \frac{d[\ln(I/T^2)]}{d(1/T)} + \frac{V_{bias}}{n}$$



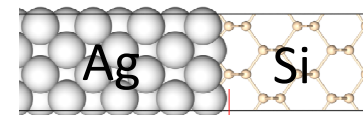
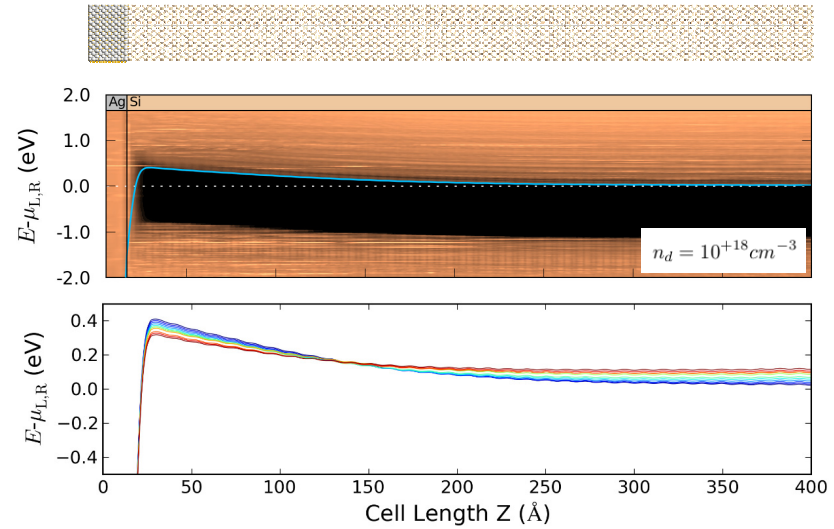
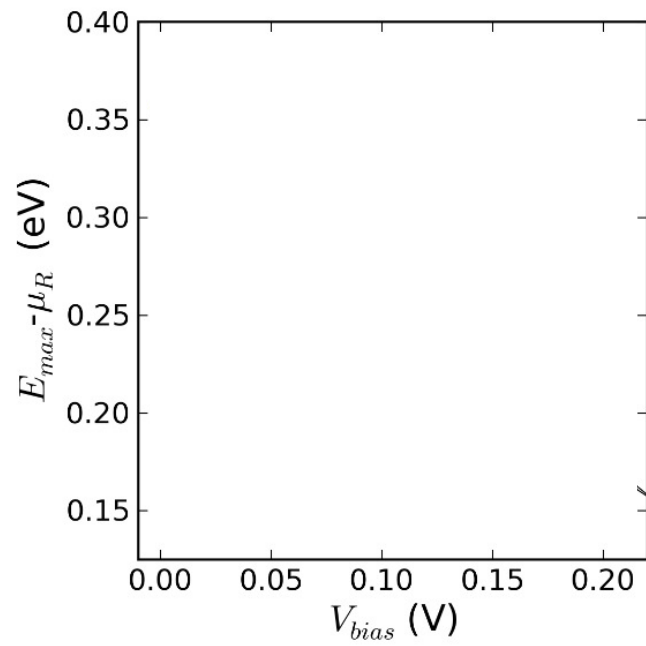
Extract the barrier from the electronic structure



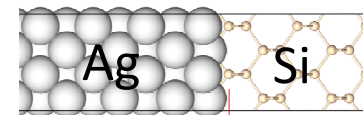
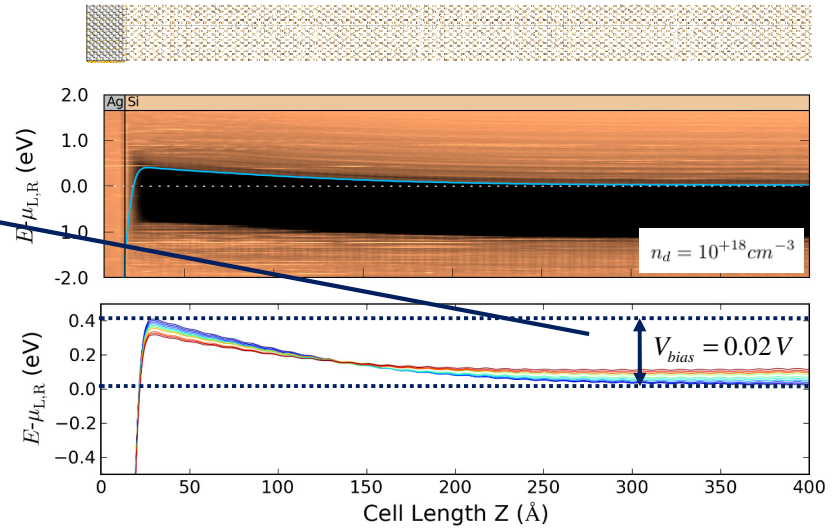
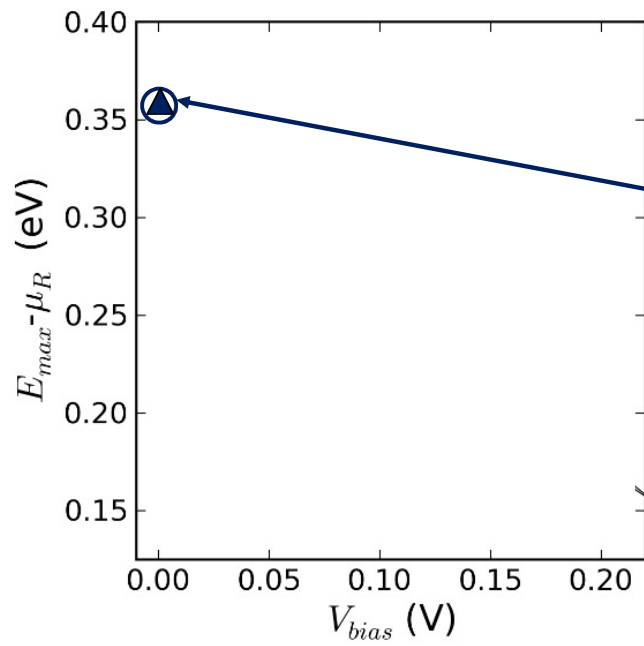
Extract the barrier from the electronic structure



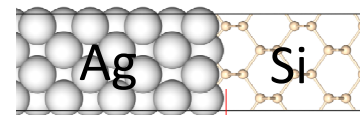
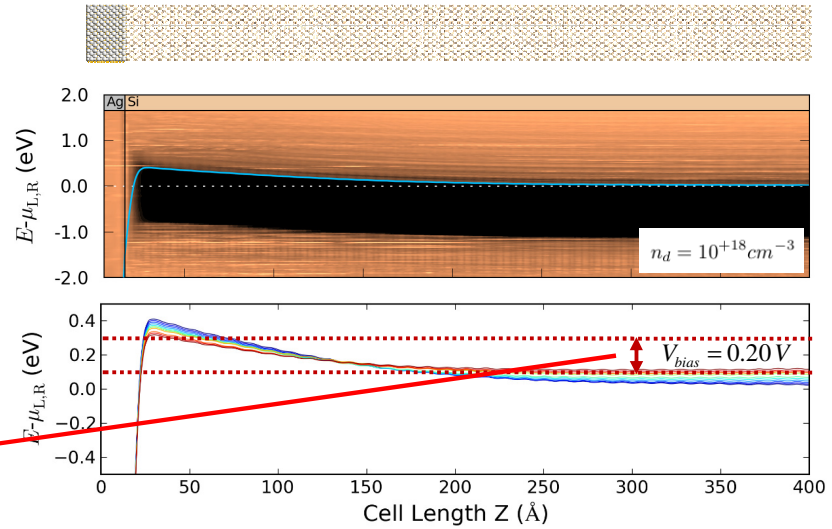
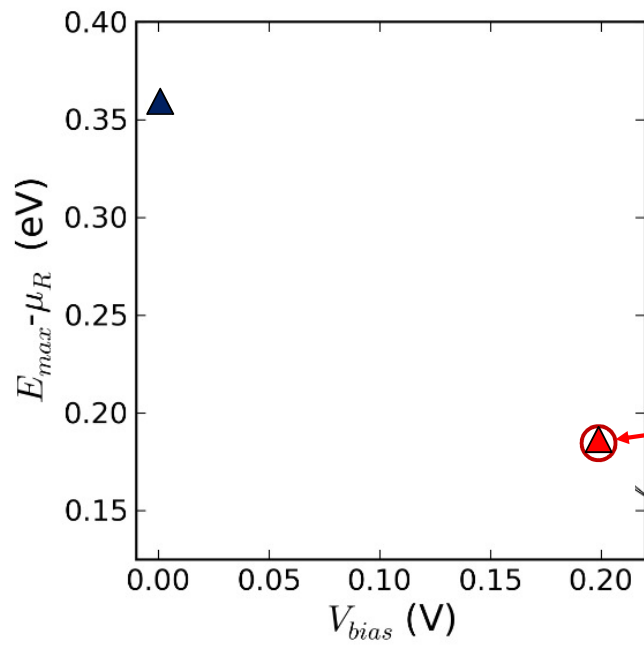
Measure the barrier height



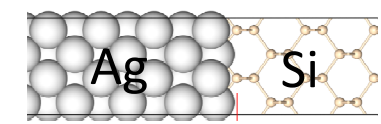
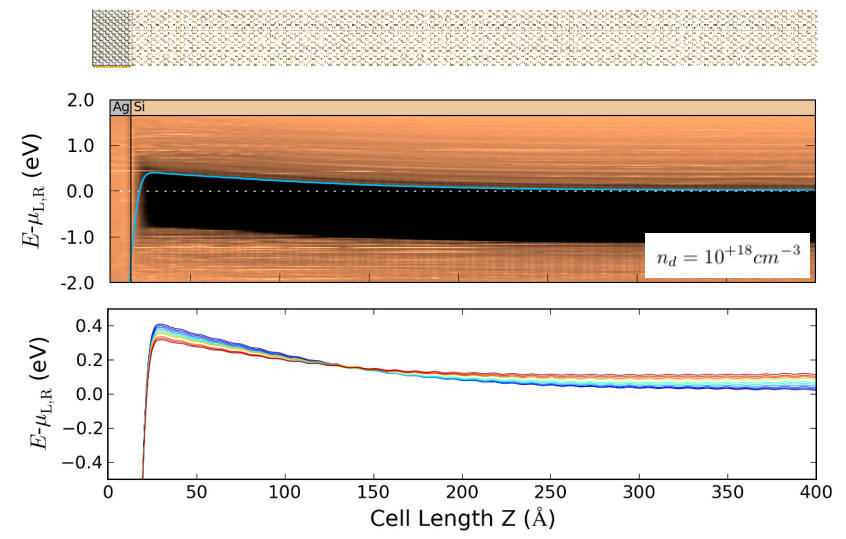
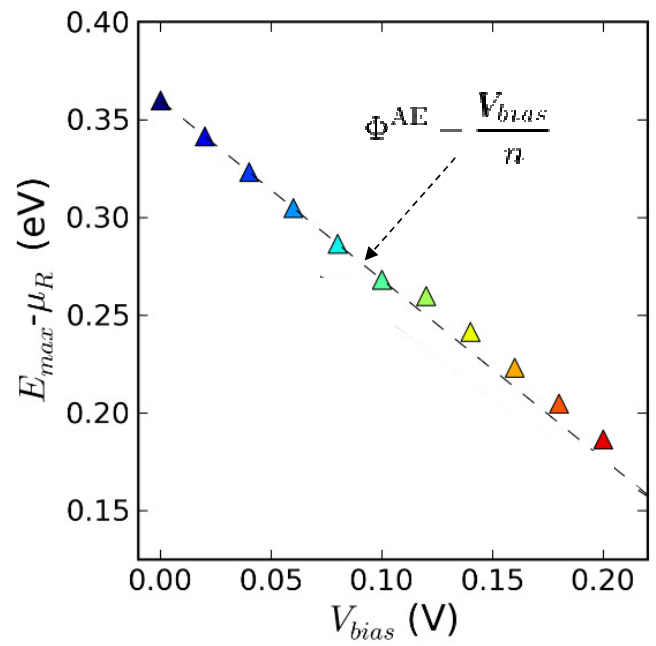
Measure the barrier height



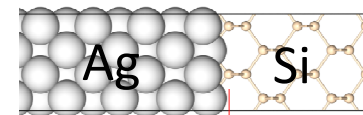
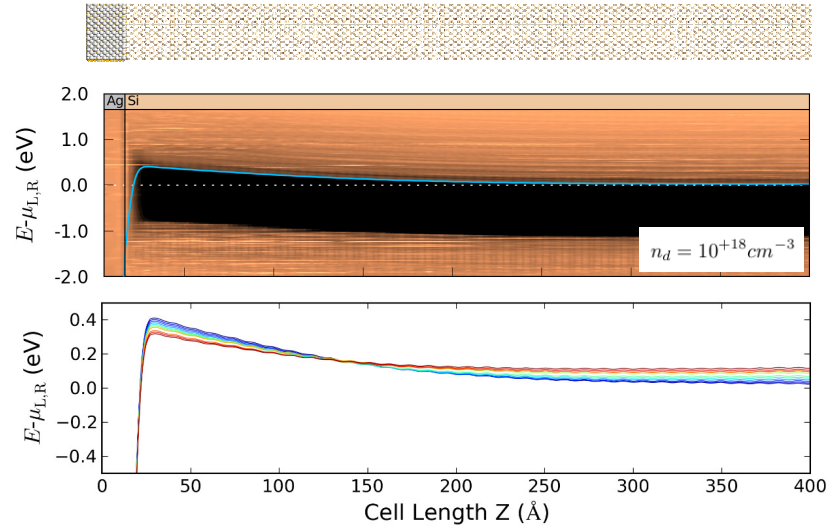
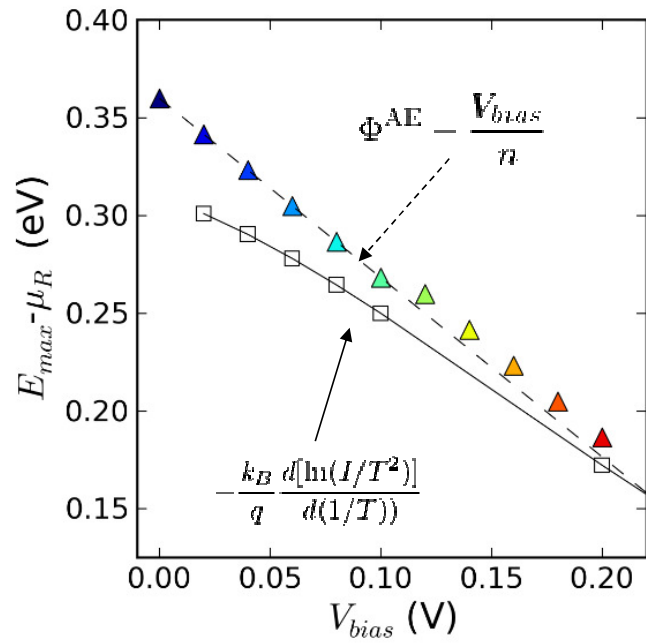
Measure the barrier height



Extract the barrier from the electronic structure

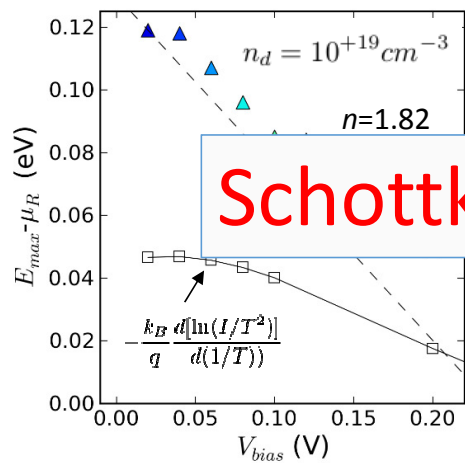
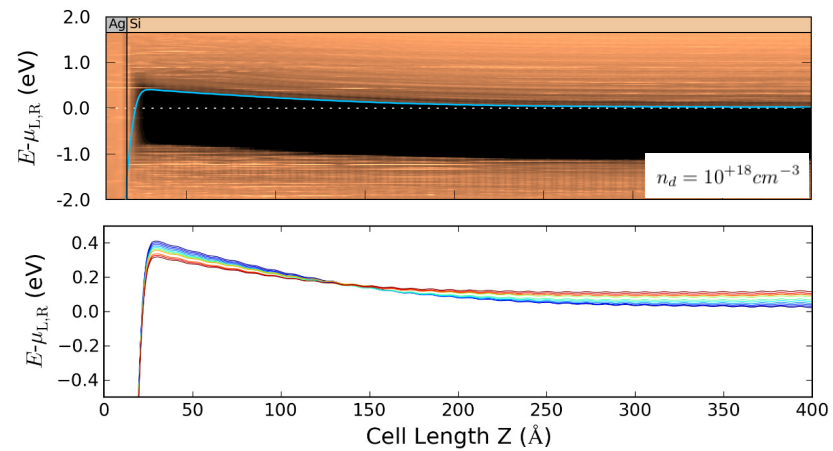
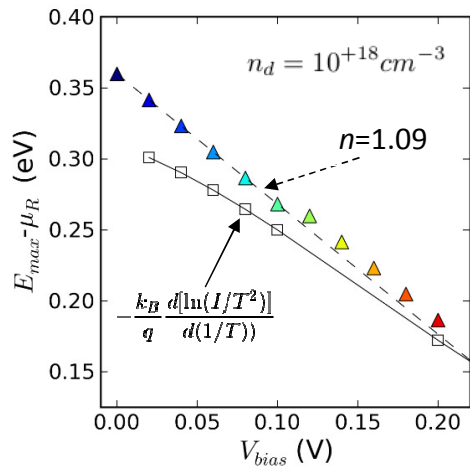


Extract the barrier from the electronic structure

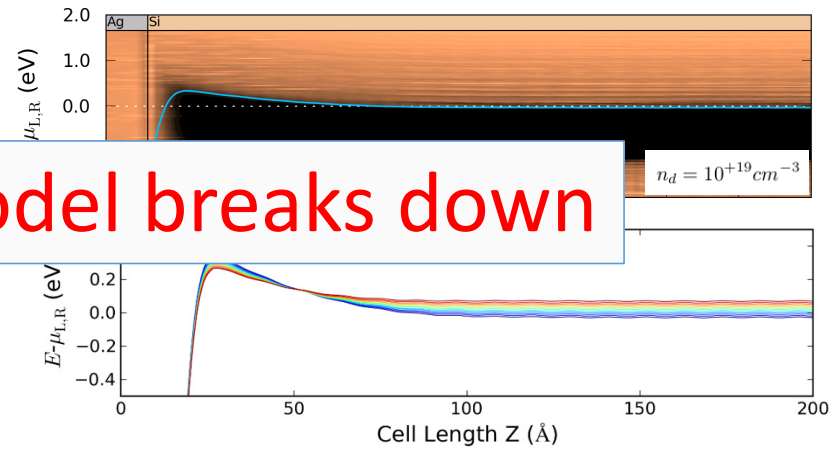




Comparison of different dopings

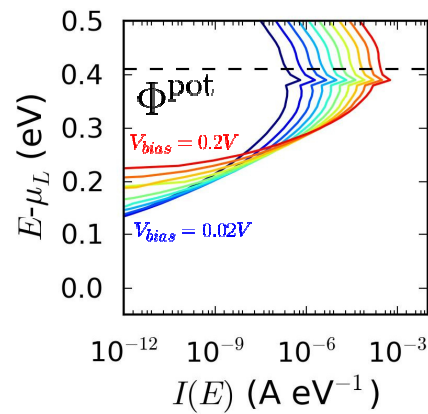
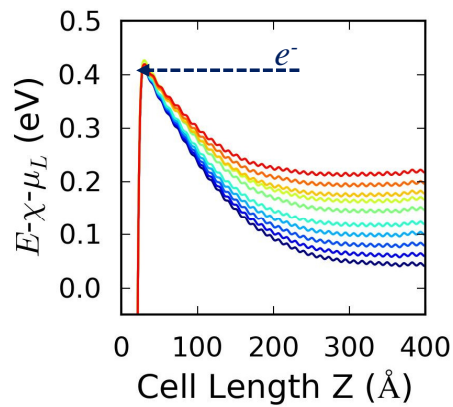


Schottky model breaks down



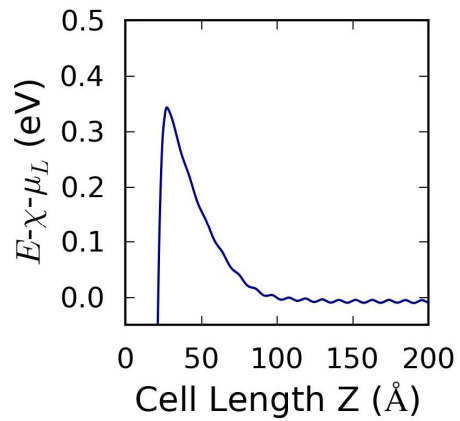


Spectral current analysis: $n_d = 10^{18} \text{ cm}^{-3}$ vs $n_d = 10^{19} \text{ cm}^{-3}$



$n_d = 10^{18} \text{ cm}^{-3}$

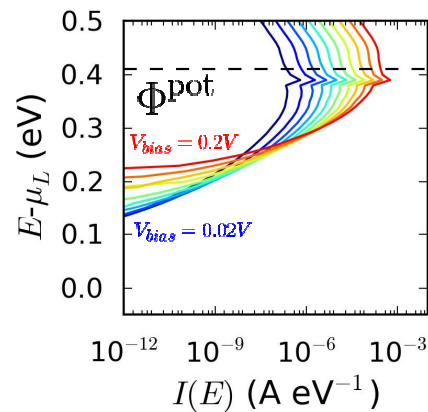
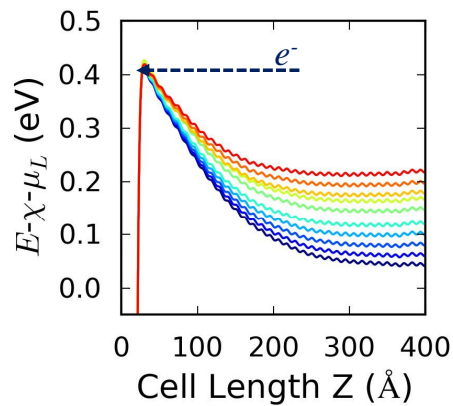
**Thermionic
emission
>>
Tunnelling**



$n_d = 10^{19} \text{ cm}^{-3}$

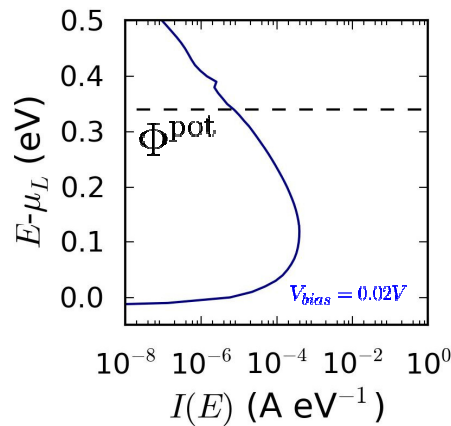
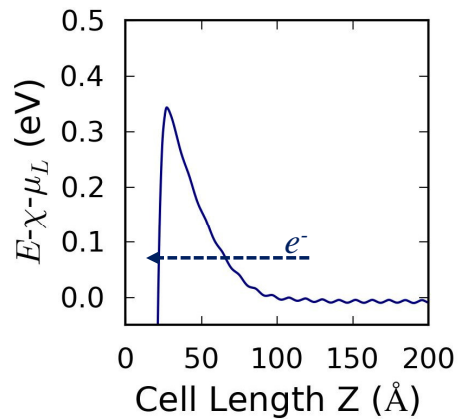


Spectral current analysis: $n_d = 10^{18} \text{ cm}^{-3}$ vs $n_d = 10^{19} \text{ cm}^{-3}$



$n_d = 10^{18} \text{ cm}^{-3}$

**Thermionic
emission
>>
Tunnelling**

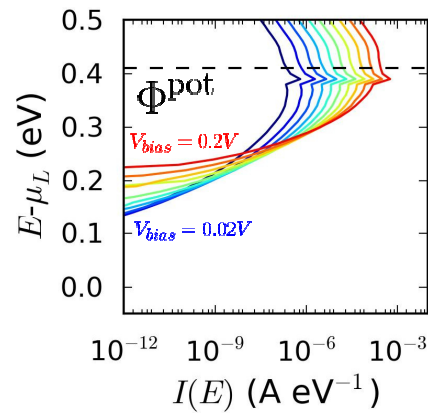
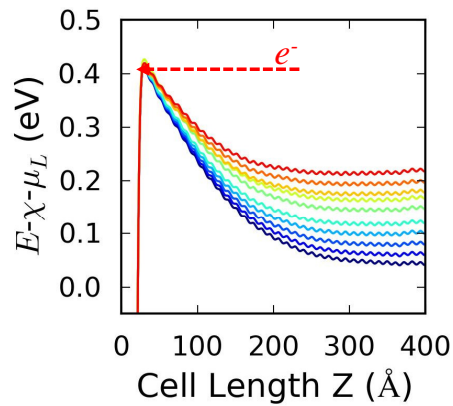


$n_d = 10^{19} \text{ cm}^{-3}$

**Tunnelling
>> Thermionic
emission**

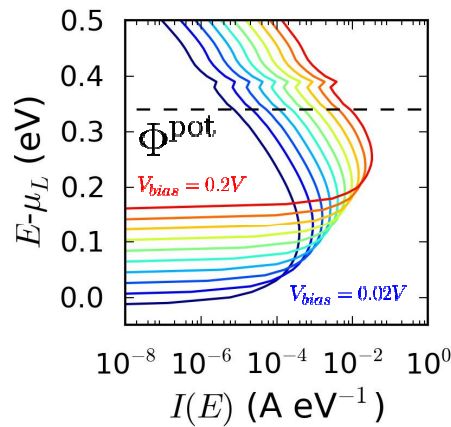
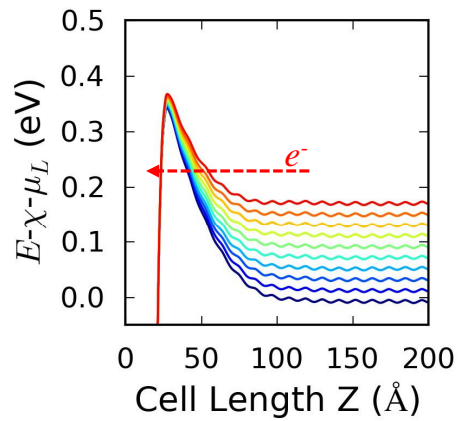


Spectral current analysis: $n_d = 10^{18} \text{ cm}^{-3}$ vs $n_d = 10^{19} \text{ cm}^{-3}$



$n_d = 10^{18} \text{ cm}^{-3}$

**Thermionic
emission
>>
Tunnelling**



$n_d = 10^{19} \text{ cm}^{-3}$

**Tunnelling
>> Thermionic
emission**

Outline

QuantumWise

Atomic-scale modelling in the semiconductor industry

Application example: Interfaces

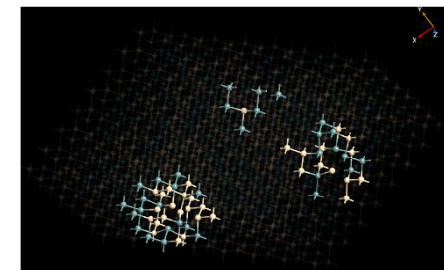
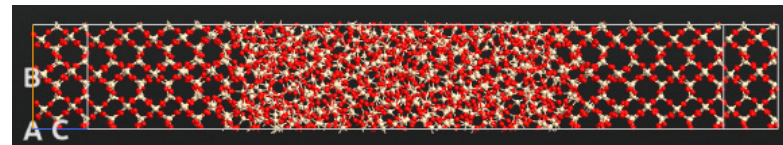
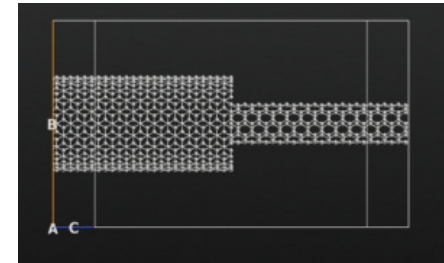
Concluding remarks





Example applications

- ⊙ Leakage currents through ultrathin gate oxide layers in MOSFETs
 - Effect of vacancies
- ⊙ Schottky barrier formation at metal-semiconductor interfaces
 - Fermi level un/pinning due to impurities in the interface
- ⊙ Contact resistance optimization
- ⊙ Properties of ultra-thin films
 - M-I-M or M-I-S structures
- ⊙ Applications in novel memory technologies
 - MRAM, ReRAM, PCRAM, atomic switches
- ⊙ Systems of reduced dimensionality
 - FinFETs
 - Nanowires (metallic and semiconducting)
 - Nanocrystals
- ⊙ Tunneling FETs
- ⊙ Exotic options
 - 2D materials
 - Nanotubes
 - Topological insulators
 - Spintronics
 - Thermionic devices
- ⊙ Strain engineering
- ⊙ Grain boundaries
- ⊙ Piezo/ferroelectric effects
- ⊙ Thermal resistance of interfaces
- ⊙ III-V and SiGe
- ⊙ Vacancy/dopant diffusion





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Author				
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Hong Li, Xin Yan, Guangfu Luo, Rui Qin, Qihang Liu, Lili Yu, Chengyong Xu, Jiaxin Zheng, Jing Zhou, Jing Lu, Zhengxiang Gao, Shigeru Nagase & Wai Ning Mei	Functionalized Metallic Single-Molecule Organic Field-Effect Transistors			
Y.W. Li, Z.L. Yin, J.H. Yao, X.S. Deng & C.L. Yang	Effect of CO adsorption on the electronic transport behavior of Fe-porphyrin molecular wire			
Chen Ling-Na, Ma Song-Shan, Ouyang Fang-Ping, Wu Xiao-Zan, Xiao Jin & Xu Hui	Negative differential resistance behaviour in N-doped crossed graphene nanoribbons	2010	Chinese Physics B Vol. 19(9), 097301	DOI URL
Ebrahim Nadimi, Philipp Plänitz, Rolf Ötting, Karsten Wiecezorek & Christian Radehaus	First Principle Calculation of the Leakage Current Through SiO ₂ and SiO _x N _y Gate Dielectrics in MOSFETs	2010	IEEE Transactions on Electron Devices Vol. 57(3), 690-695	DOI
E. Nadimi, P. Plänitz, R. Ötting, M. Schreiber & C. Radehaus	Single and Multiple Oxygen Vacancies in Ultrathin SiO ₂ Gate Dielectric and Their Influence on the Leakage Current: An Ab Initio Investigation	2010	IEEE Electron Device Letters Vol. 31(8), 881-883	DOI
Yun Ren, Ke-Qiu Chen, Jun He, Li-Ming Tang, Anlian Pan, B.S. Zou & Yan Zhang	Mechanically and electronically controlled molecular switch behavior in a compound molecular device	2010	Appl. Phys. Lett. Vol. 97(10), 103506-3	DOI URL

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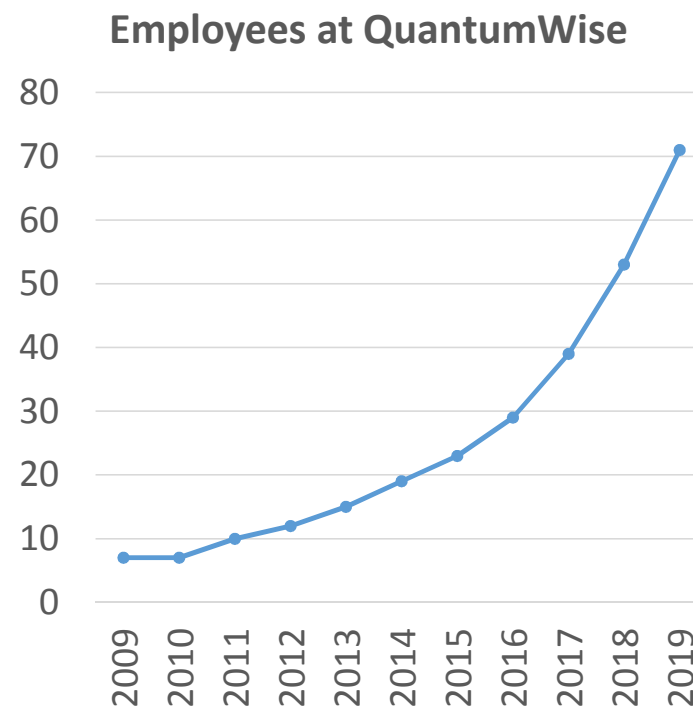
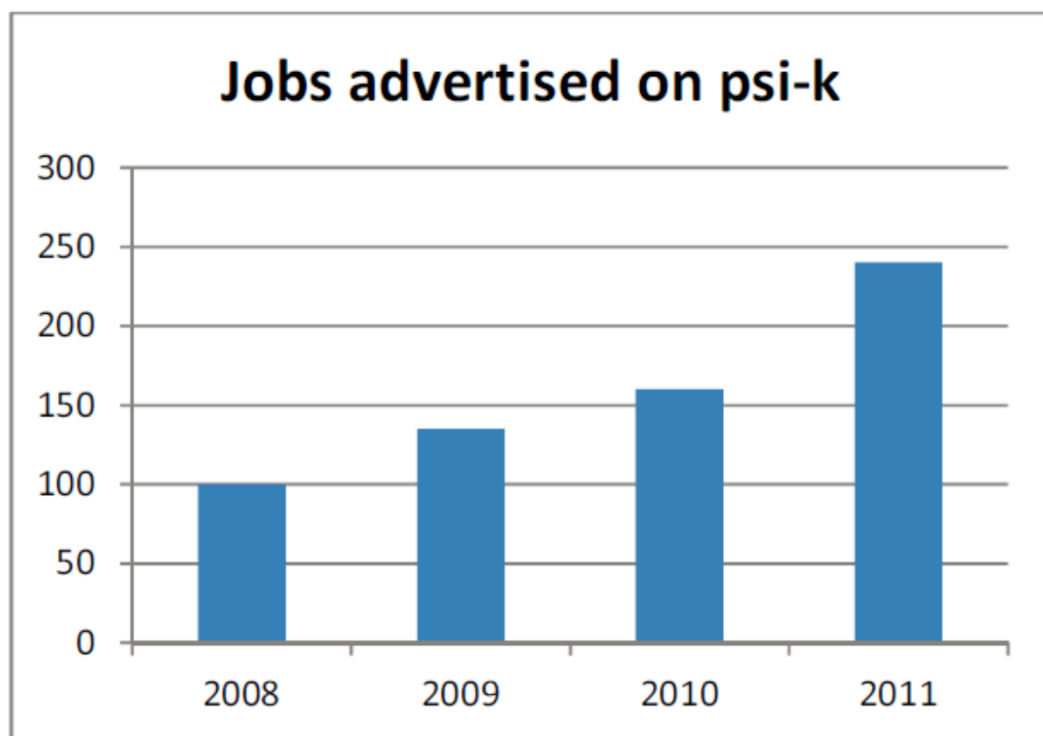
Materials, surfaces and chemistry

Conclusions from the EMMC



1. Discrete models are well established in the major chemical companies (BASF, Dupont, Dow, Sumitomo Chemical) since several decades. The expansion to smaller chemical companies is slow.
2. The use of e/a/m modelling in industries dealing with solid state materials is emerging
3. The key bottlenecks are
 - Shortcomings in the intrinsic capabilities
 - Lack of industry-ready integrated, standardized, interoperable software solutions
 - **Lack of trained translators**
 - Coupling between the atomistic and the continuum scales
4. Government investments are often guided by academic objectives, not progressing the transfer of modelling software to industrial endusers
5. Continuum modelling is well established with a few large commercial software owners. Discrete models is less established with many scattered small commercial and academic software owners.
6. Strong academic community in Europe within discrete models.

High demand for experts in electronic-structure theory



44 jobs announced during the last month

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